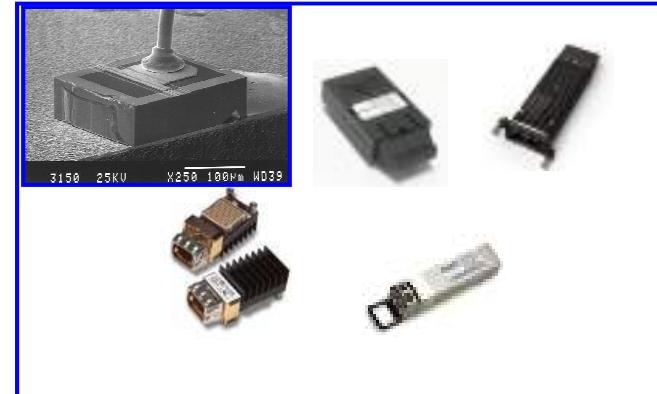


# Semiconductor lasers for optical communication

*Roberto Paoletti*

*R&D, Testing and Reliability Manager*

*Avago Technologies Italy*

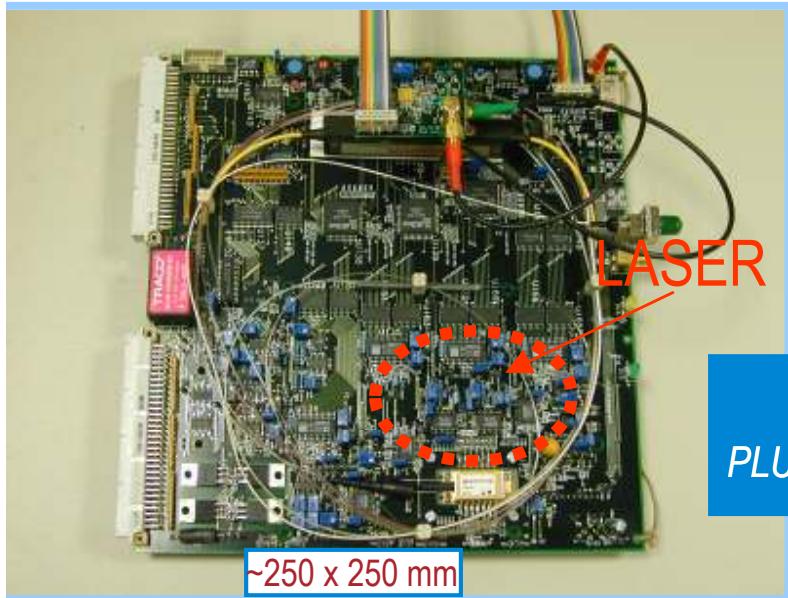


- Laser sources for “*pluggable transceiver world*”
  - Design for performances
  - Fast lasers
- Transceiver for next generation networks
- *Torino Technology Center - Avago Technologies Italy*

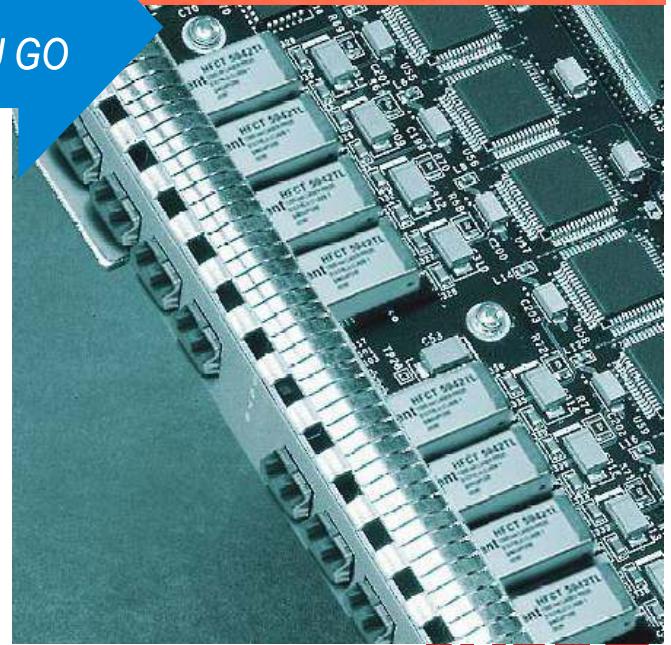


# Pluggability: a keyword...

*From transceiver cards to hot-pluggable transceiver modules*



Evolution (since 2000)  
PLUGGABILITY: PAY AS YOU GO

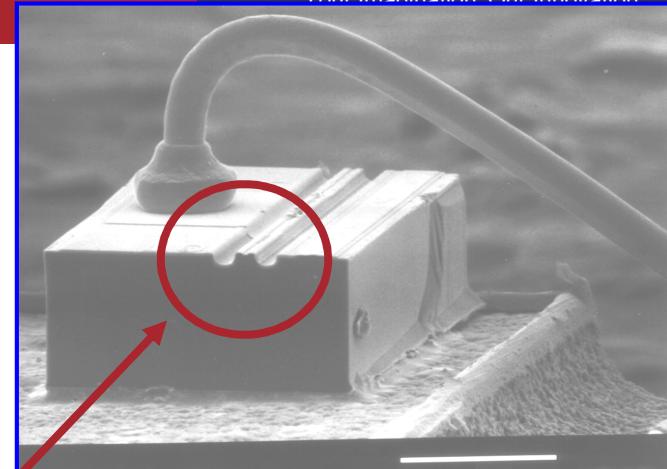


- Strong limits in space available and power budget
- Wide temperature operation ( $0 \div 85^\circ\text{C}$ )

⇒ Requirement on lasers:

- High temperature operation (preferably uncooled)
- Low cost, high manufacturing yield, high reliability
- no compromise on High performance  
(high bit rate, high optical power, high spectral purity, ...)

# Semiconductor Laser is:



Active material



***Semiconductor layer with optical gain***

Carrier population generation



***Electrical injection***

Cavity



***Crystal Mirrors (FP)  
or Grating (DFB – DBR)***

electrical



**Heterojunction**

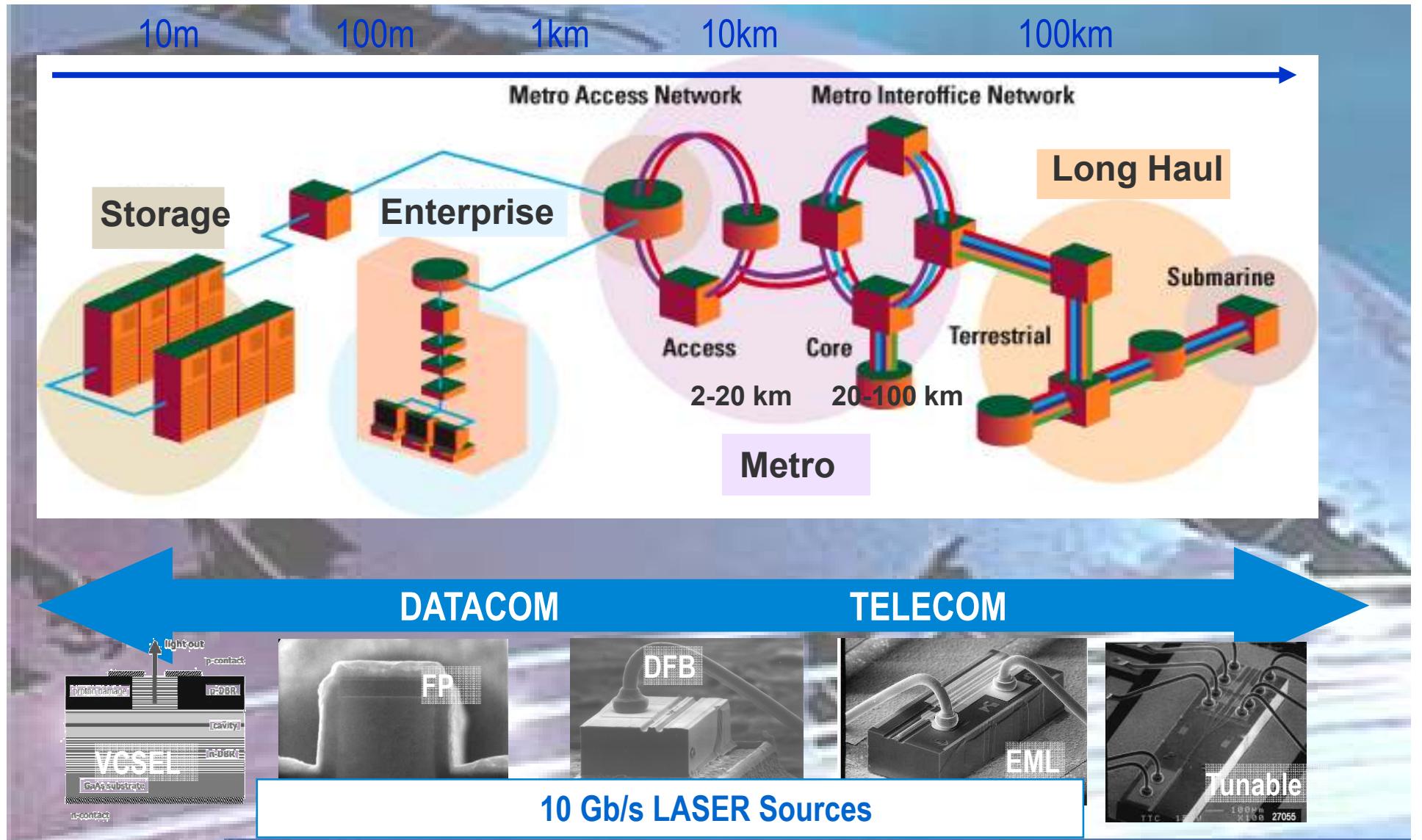
Confinements:

optical

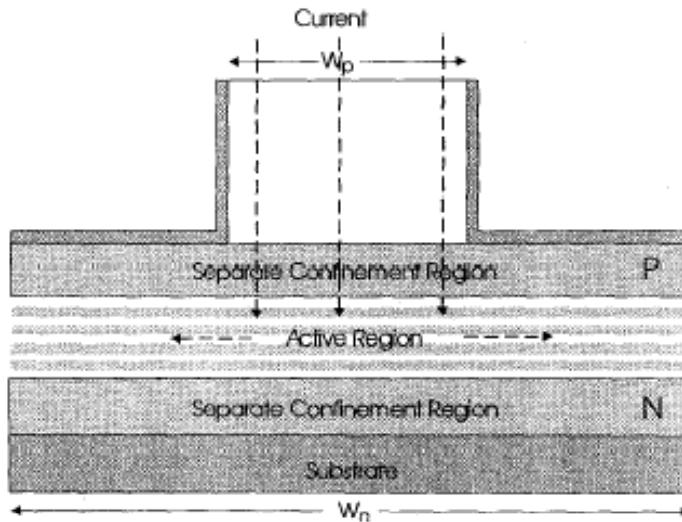


**Optical waveguide**

# Lasers for Optical Networks



# Design for performance (ridge )

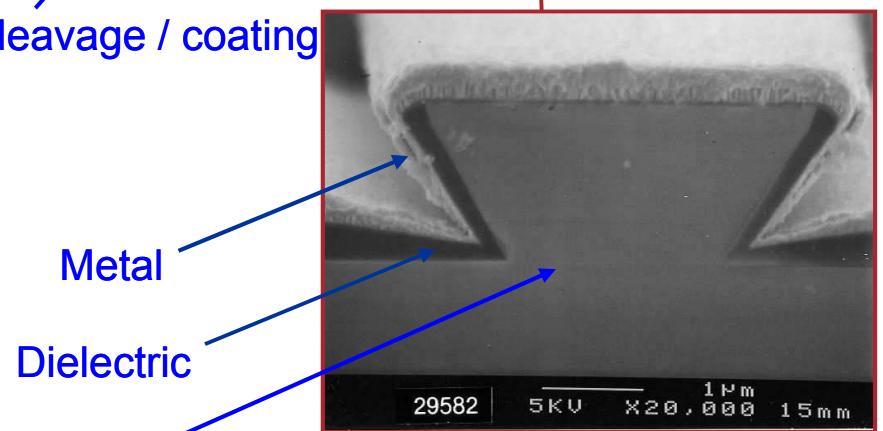
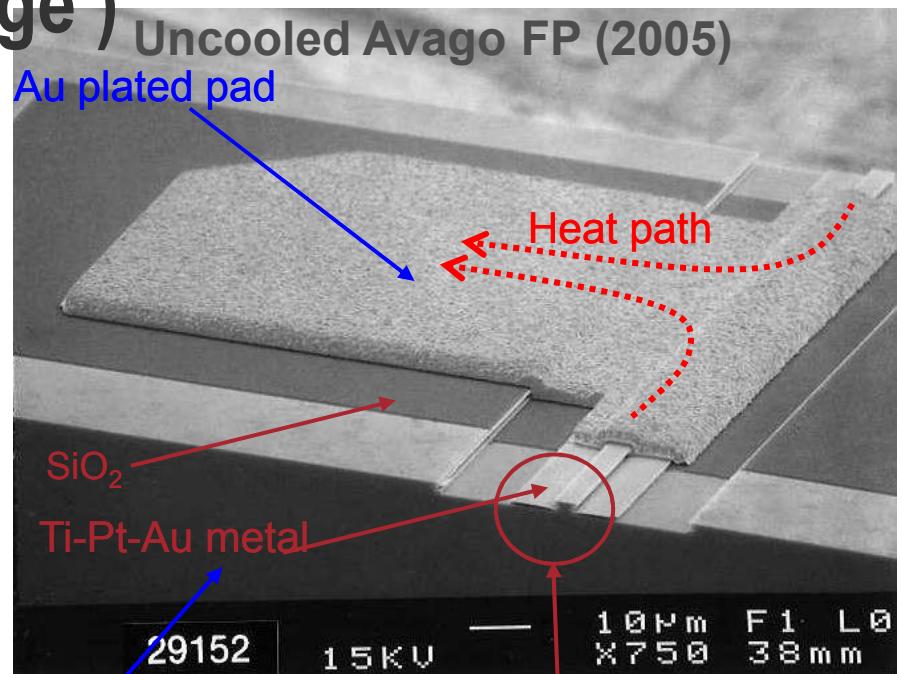


## Ridge structure

No lateral blocking layers  $\Rightarrow$

- Very simple technological process (one-step epi-growth)
- Suitable for Al-based lasers and low cost devices

Optimised facet cleavage / coating

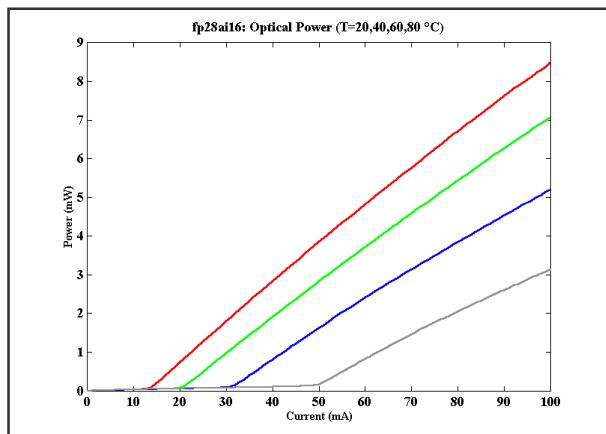


Narrow reverse mesa (Low Rs, small cavity, fast chips)

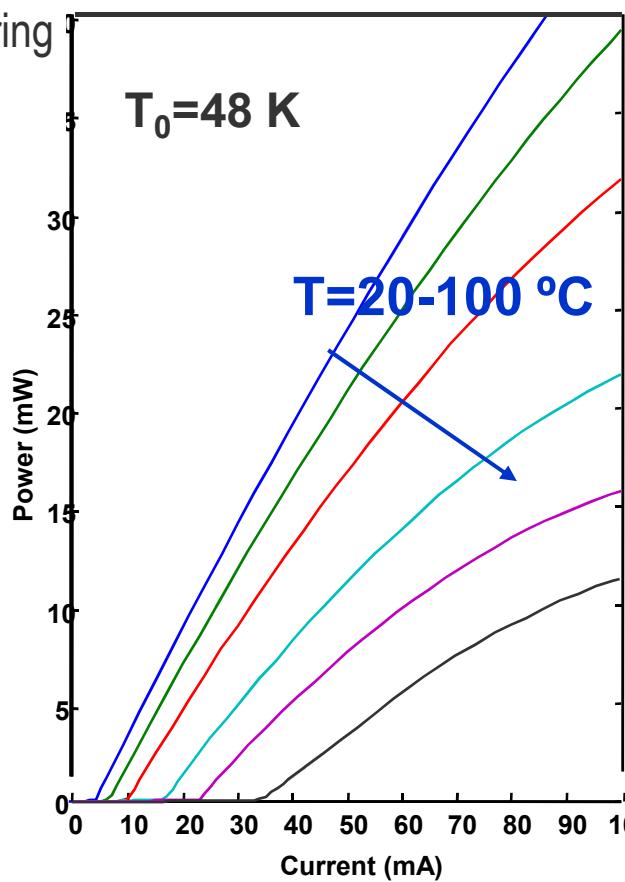
R. Paoletti, 11/2011

# Active material: long path of performance improvement

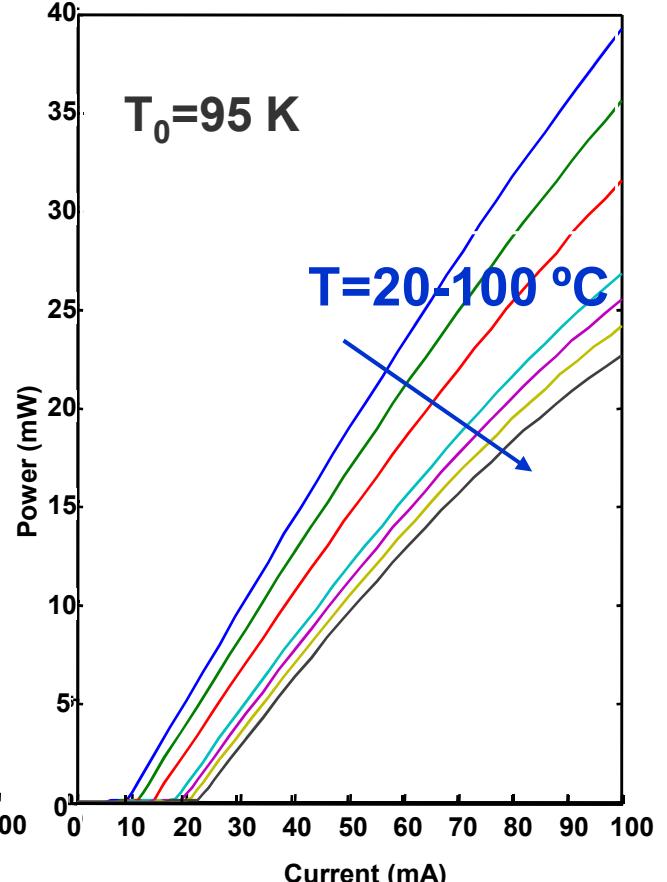
10 years of active material engineering leads to massive improvement of temperature performance



InGaAsP Bulk material (50 mA  
Threshold at 80°C, CSELT, 1995)



InGaAsP-based MQW  
(Agilent, 2001)



InGaAsAl-based MQW  
(Avago, 2005)

# Modulation schemes for datacom/transport NW

## *Transmit information:*

⇒ Frequency/Phase Modulation of laser source: transport NW.

⇒ Intensity modulation of laser source



- Intensity modulation by:

- External modulator: ⇒ expensive



(long haul only)

- Direct modulation: ⇒ cheap/simple

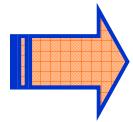


⇒ short haul



(1.55um <200 km @ 2.5 Gb, 30 km @ 10Gb; <25 km 1300nm)

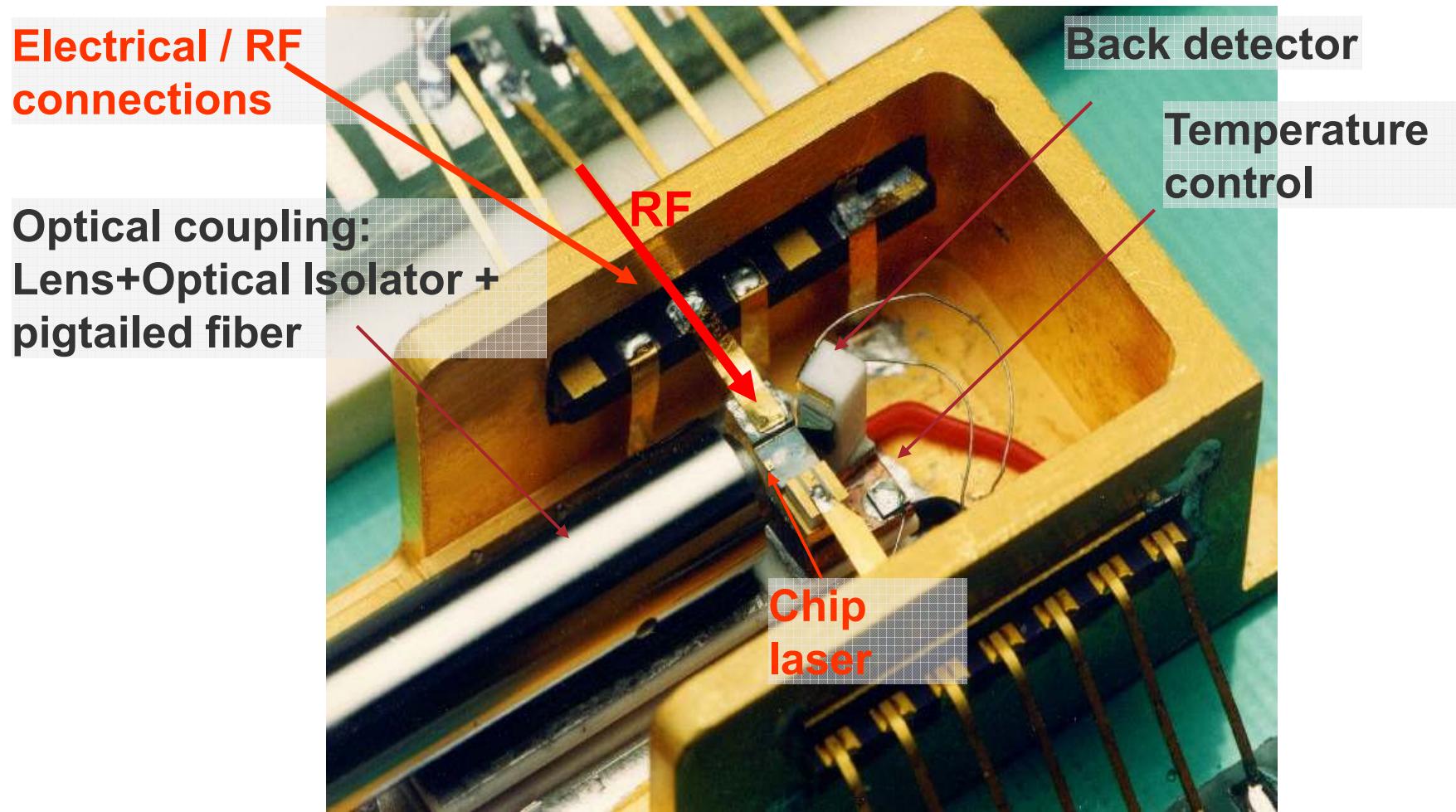
⇒ need high speed devices



**So we want uncooled, low cost laser ... and fast!!!**

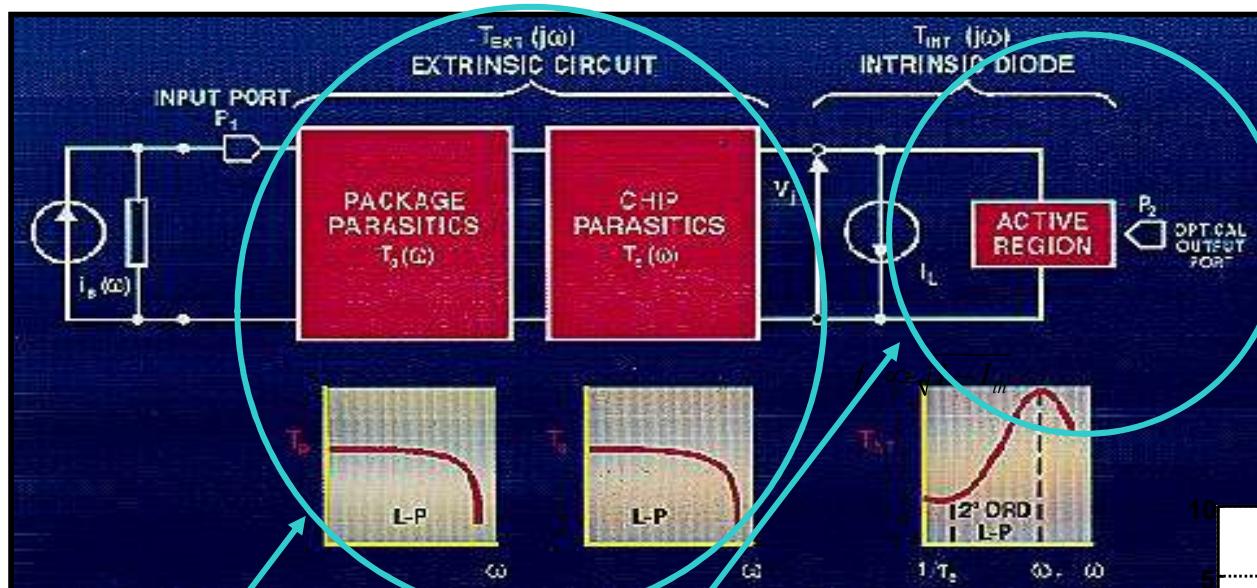
# Direct Modulation of Laser Module

## *Butterfly Laser Module, (1990 – 2000)*



# Intensity modulation of laser sources

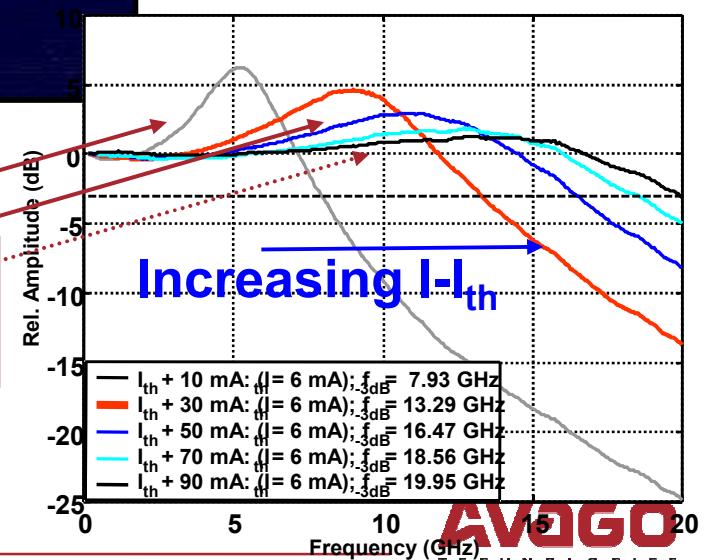
- Laser chip equivalent circuit



Parasitics

Active material

$$f_r \propto \sqrt{I - I_{th}}$$



# Direct Modulation of Laser Module

*Electro-optical measurement and simulation (1994) for bandwidth optimization*

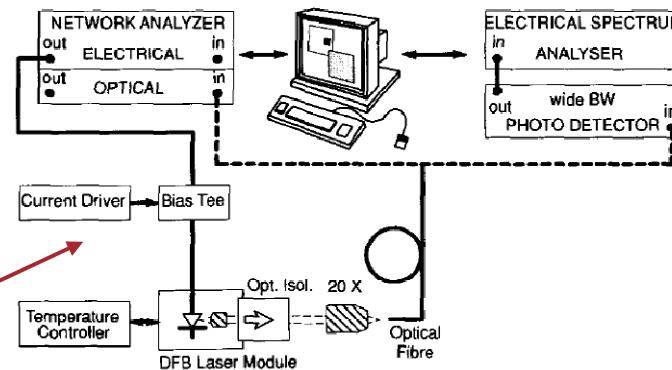
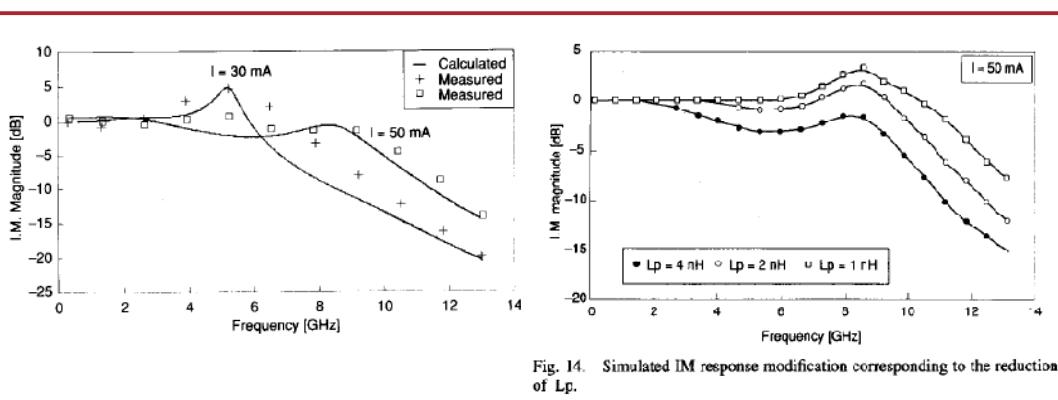


Fig. 5. Measurements setup.



F. Delpiano, R. Paoletti, P. Audagnotto and M. Puleo; High Frequency Modeling and Characterization of High Performance DFB Laser Modules; IEEE TRANS ON COMPONENTS, PACKAGING, AND MANUFACTURING TECHNOLOGY, VOL. 17, NO. 3, AUGUST 1994

E/O  $S_{21}$

Elec.  $S_{11}$

RIN,  
Optical  $S_{21}$

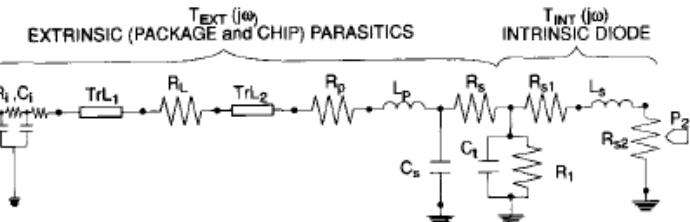
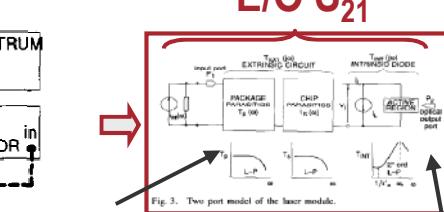
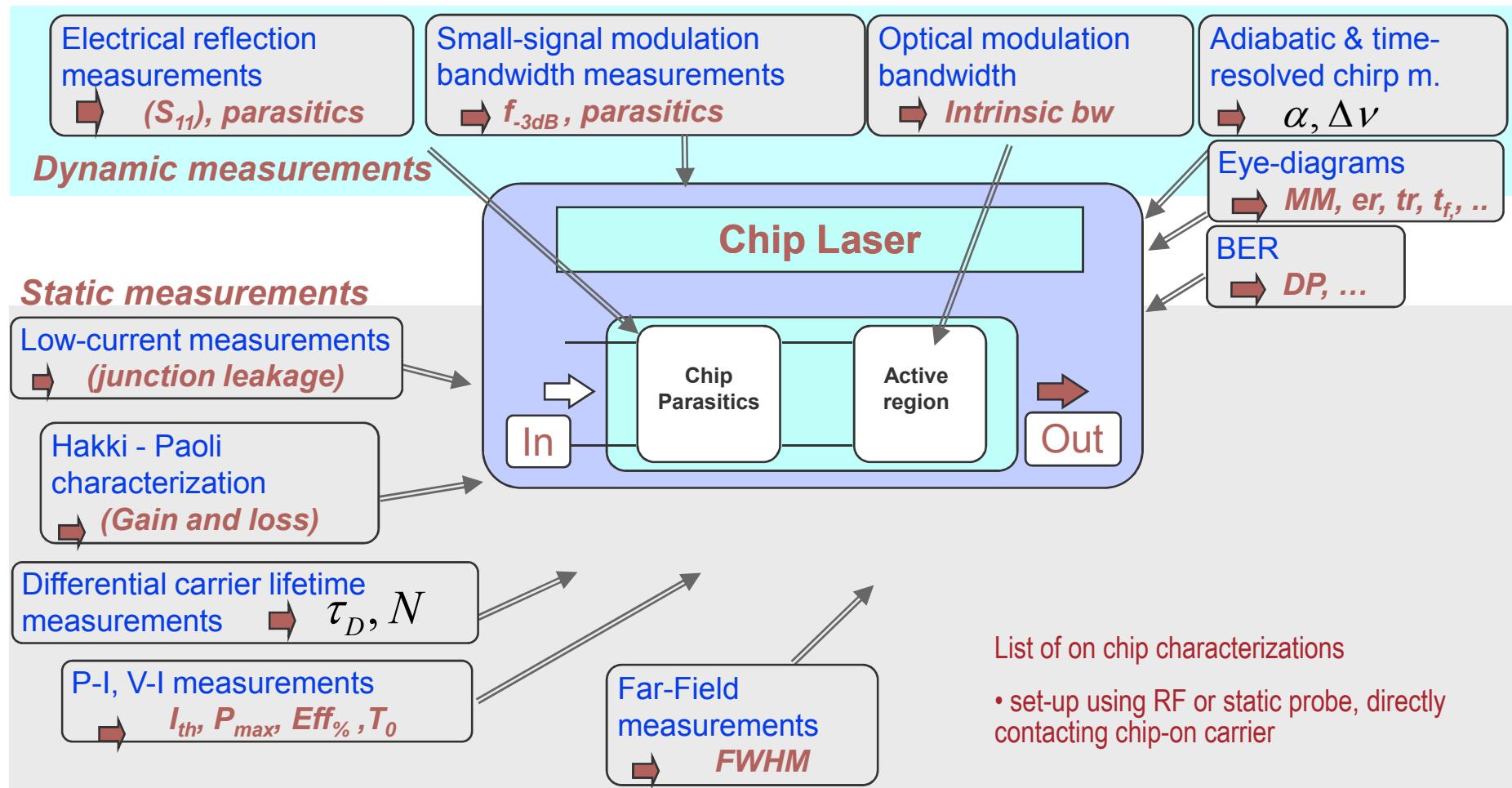


Fig. 10. Complete equivalent circuit of the laser module.

# Laser chip optimization

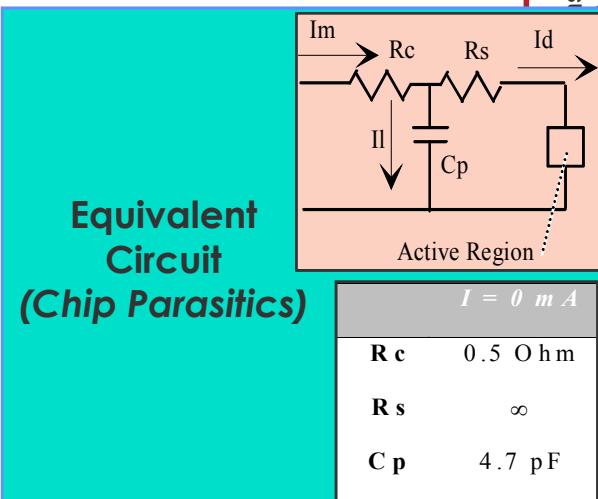
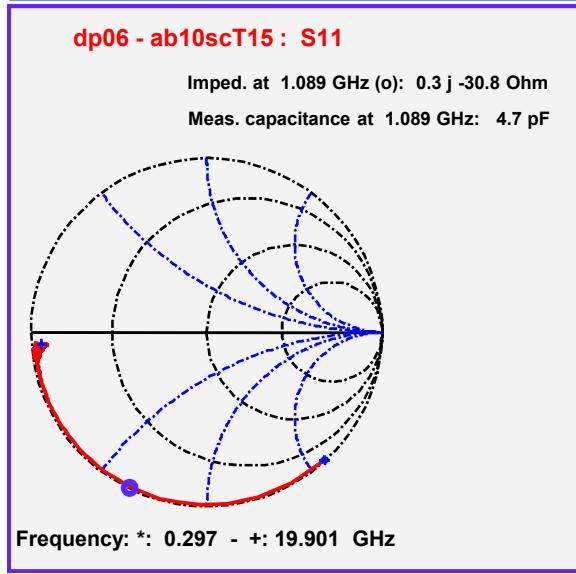
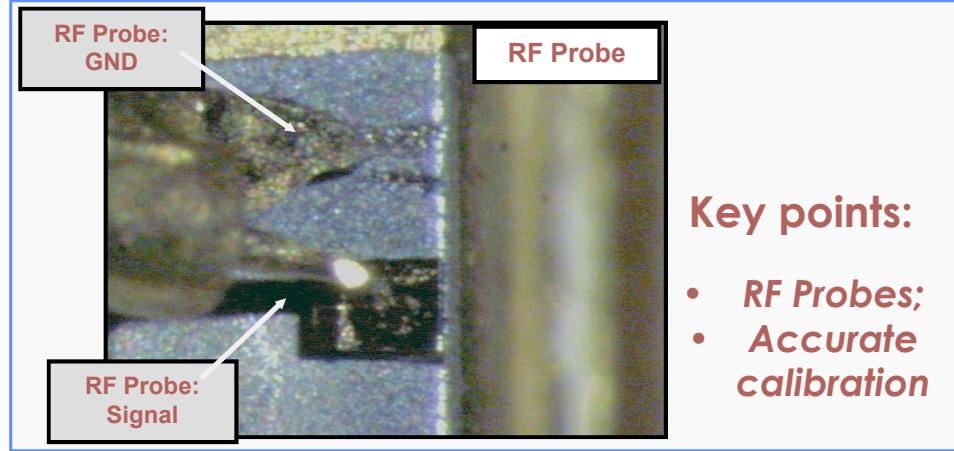
*On-chip static and dynamic characterizations, on dedicated optical benches.*



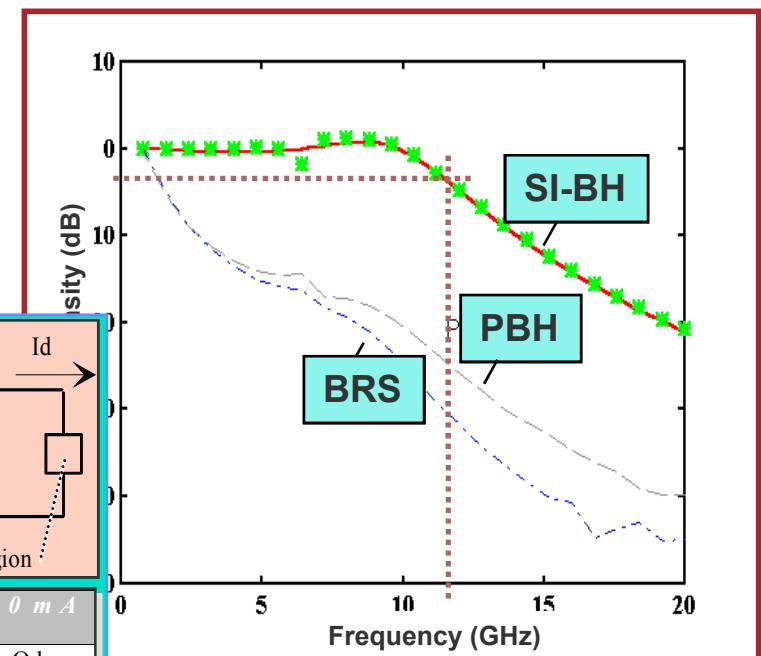
# Direct RF Probing of laser chip:

*Chip parasitics analysis on SI-BH (1995)*

- Parasitics analysis by  $S_{11}$  measurement: a long story ...



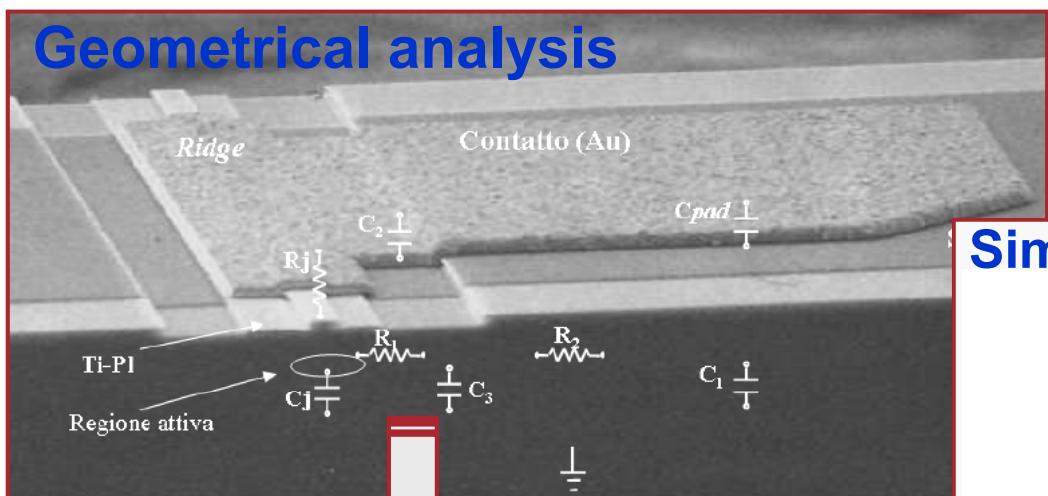
First 0-20GHz  $S_{11}$  –  $S_{21}$  measurements  
by custom designed RF probe (1995)



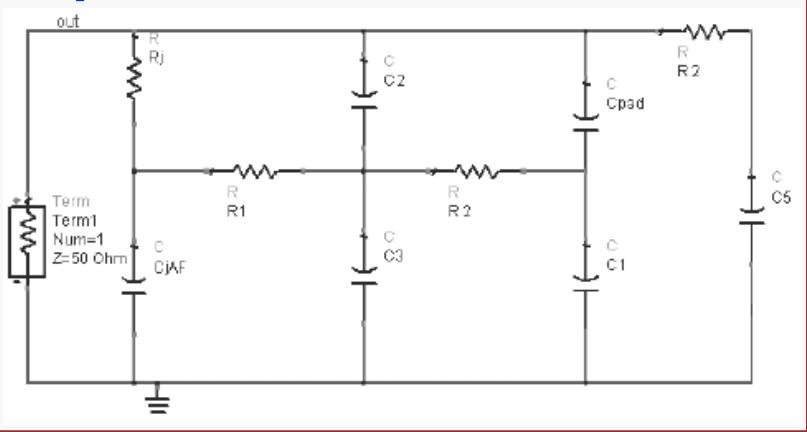
# Laser chip RF optimization: direct RF probing of laser chip

*Chip parasitics on Ridge Structure, ADS model,  $S_{11}$  measurements*

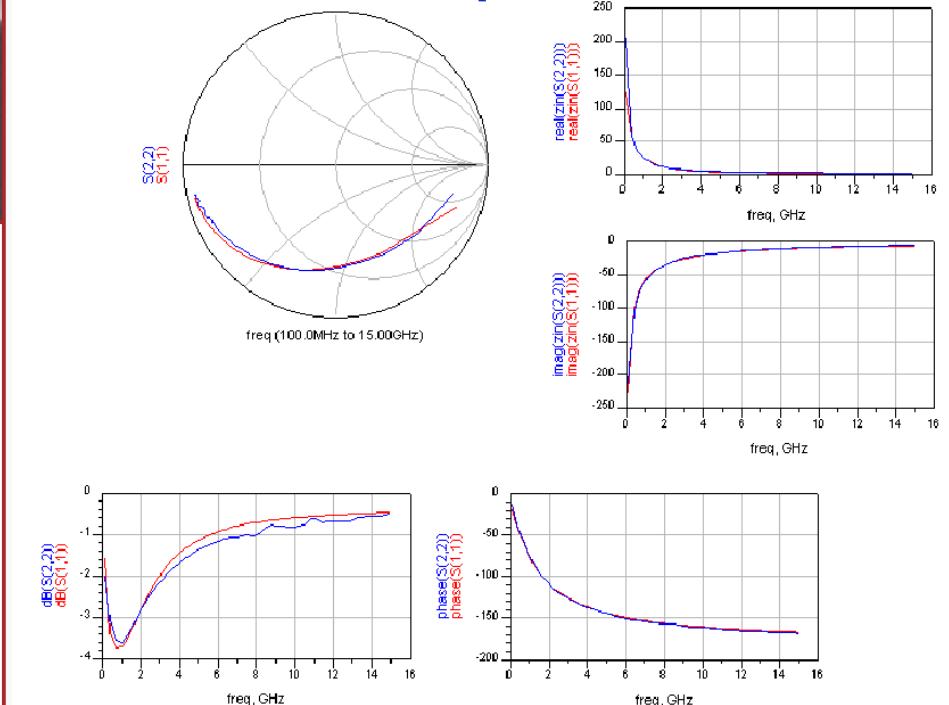
## Geometrical analysis



## Equivalent circuit

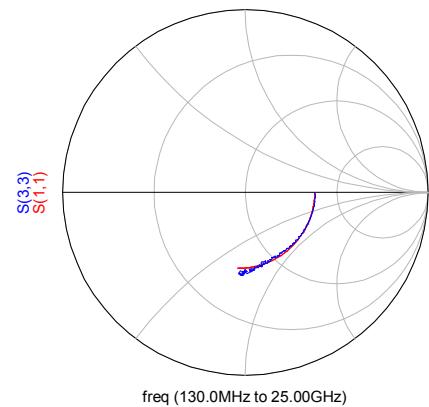


## Simulation and experimental results

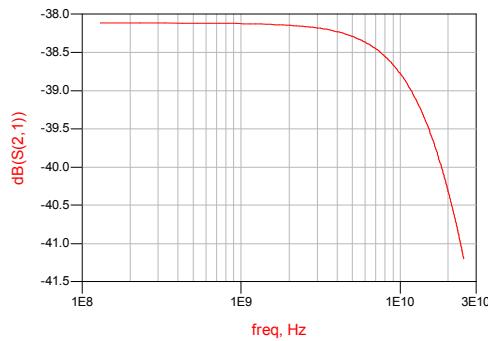


# Direct RF Probing of laser chip:

## VCSEL $S_{11}$ modeling (ADS)

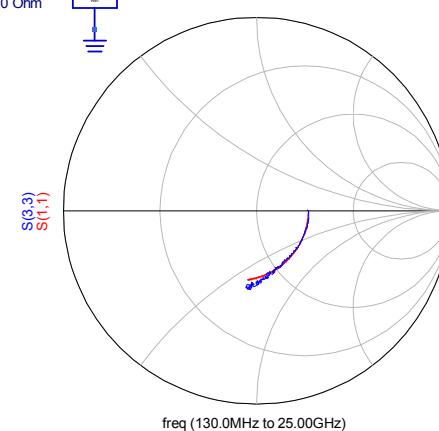
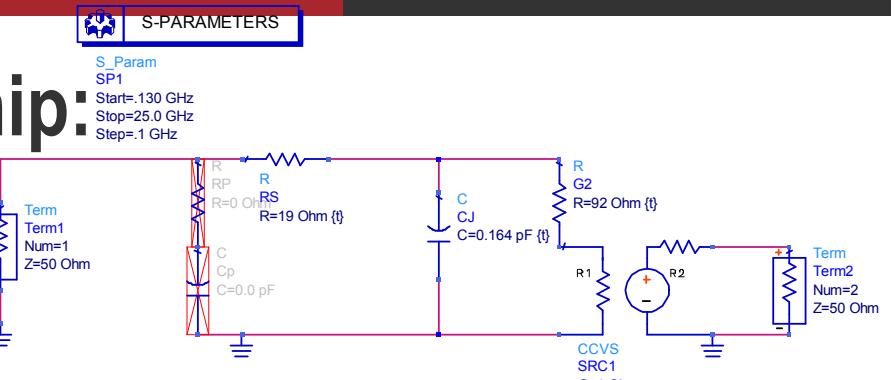


4 mA S11  
parameter  
extraction

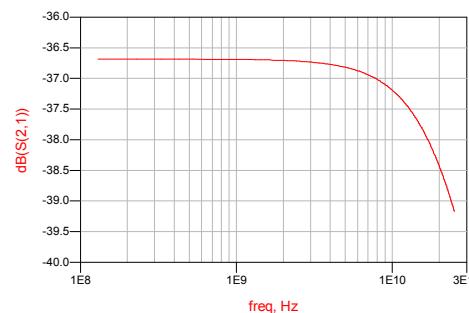


Expected parasitic  $S_{21}$   
 $>25$  GHz

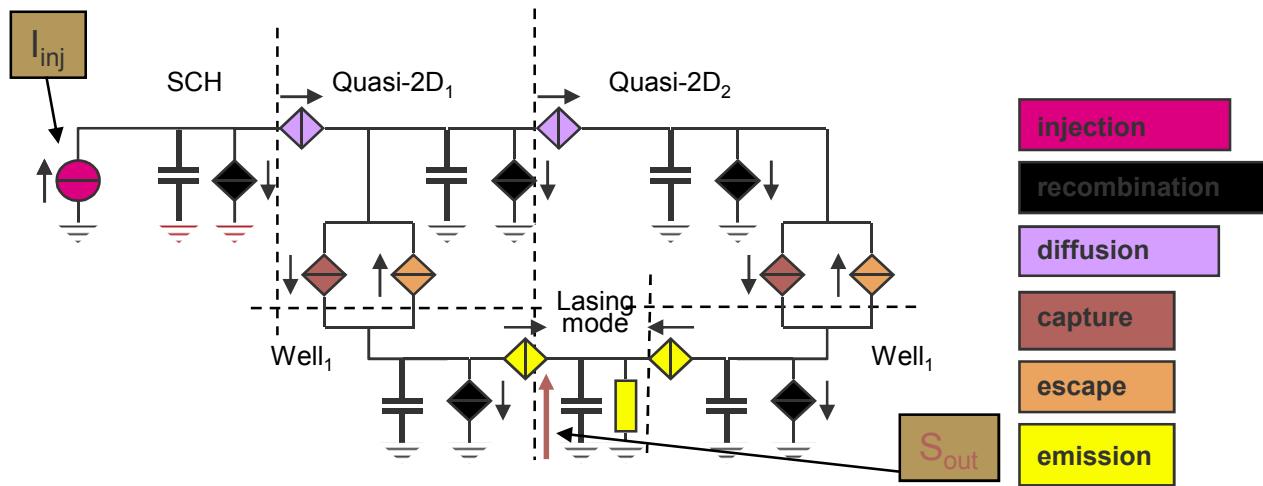
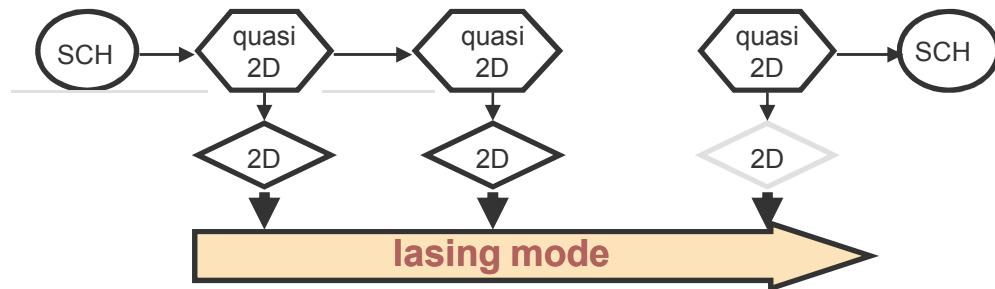
Set up: N4376B. Cascade probe + substrate calibration



8 mA S11  
parameter  
extraction



# Intensity modulation of laser source MQW active layer ADS model



G. Rossi, R. Paoletti, M. Meliga, "SPICE simulation for analysis and design of fast  $1.55 \mu\text{m}$  MQW laser diodes", IEEE Journal of Lightwave Technology, Vol. 16, No. 7, July 1998

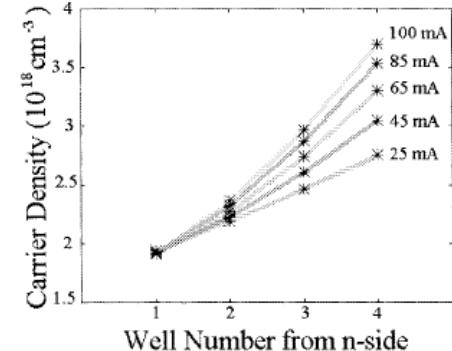


Fig. 8. Carrier injection nonuniformity in a four-QW laser at different bias points.

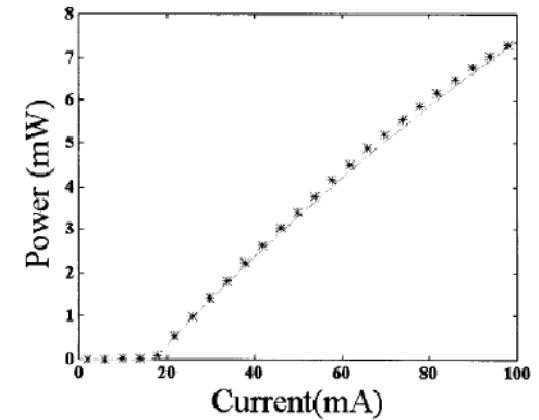
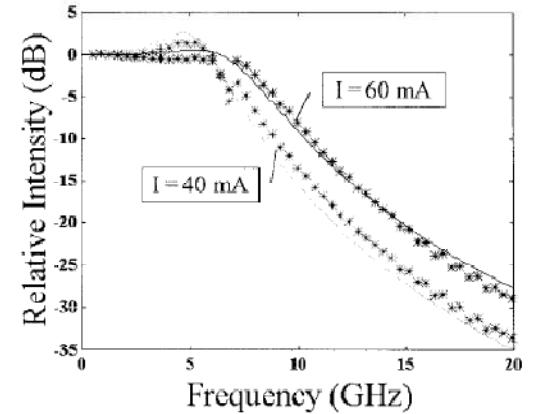
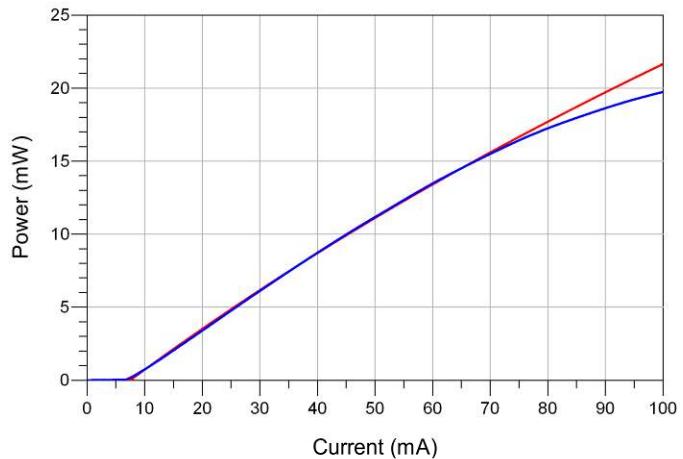


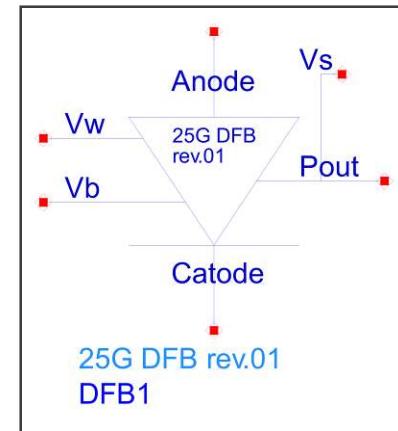
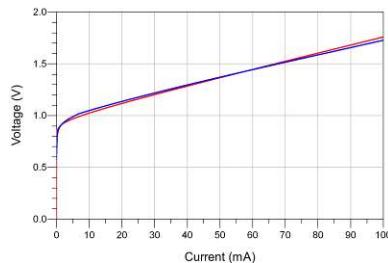
Fig. 11. Static characteristic for a  $400\text{-}\mu\text{m}$  long device at  $20^\circ\text{C}$  (Process A). Asterisks stands for data and continuous line for simulation.



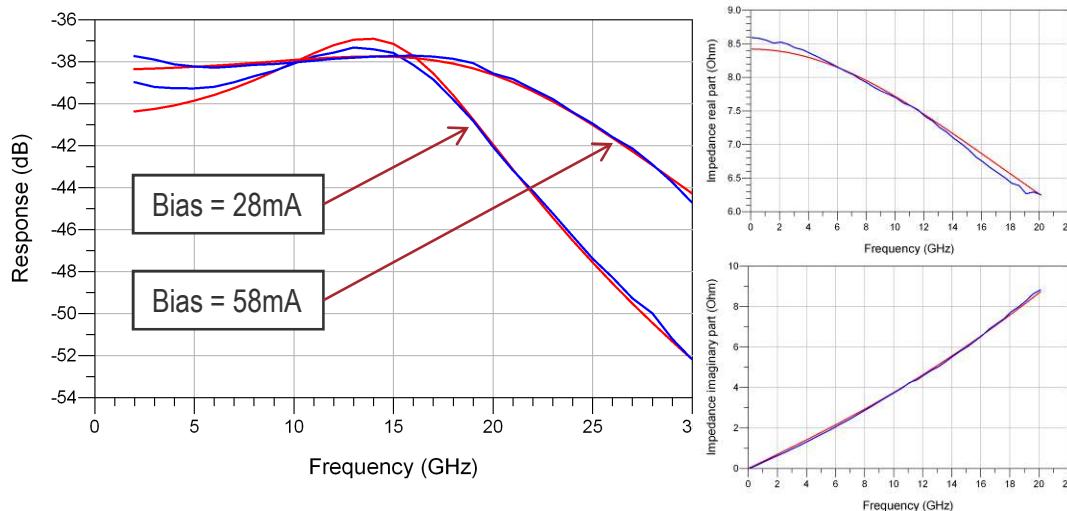
# ADS model: simulation (red) vs. measurements (blue)



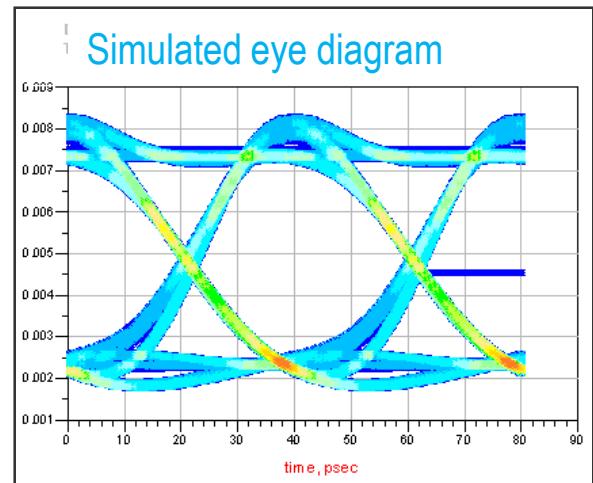
LIV curves



S parameters (bandwidth and dynamic impedance)



Simulated eye diagram



# Direct Modulation of TOSA

## *Electro-optical measurement and simulation*

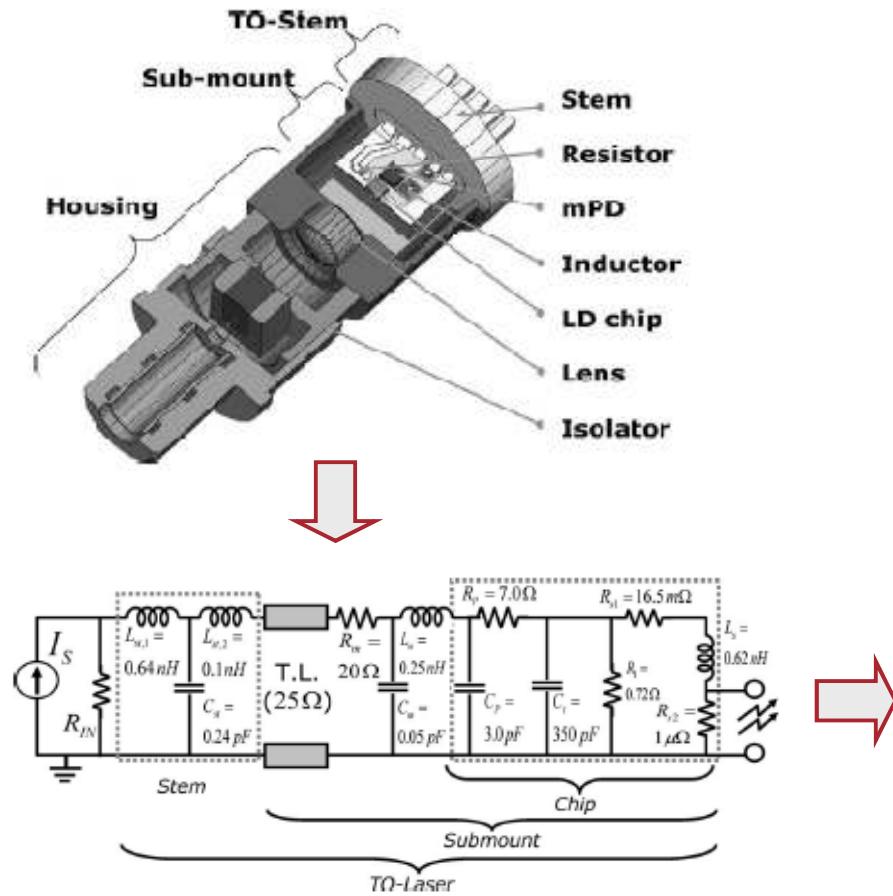
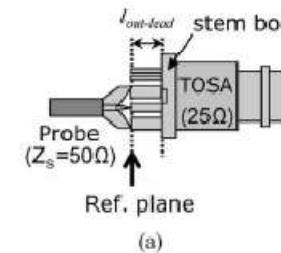
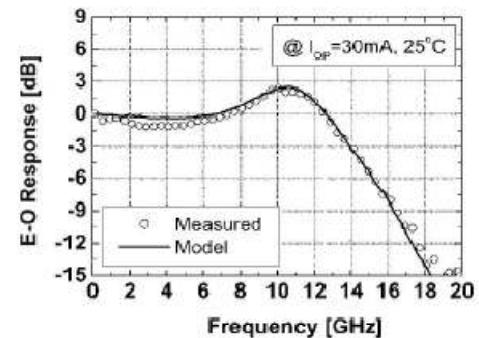


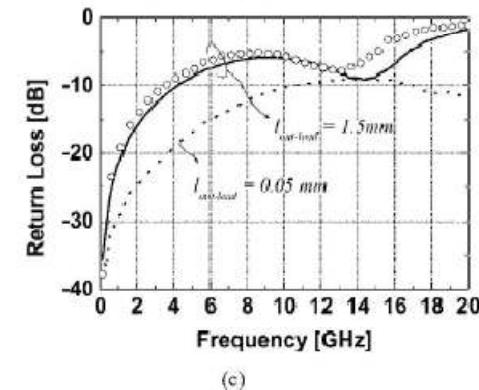
Fig. 10. Equivalent circuit model of the TOSA.



(a)



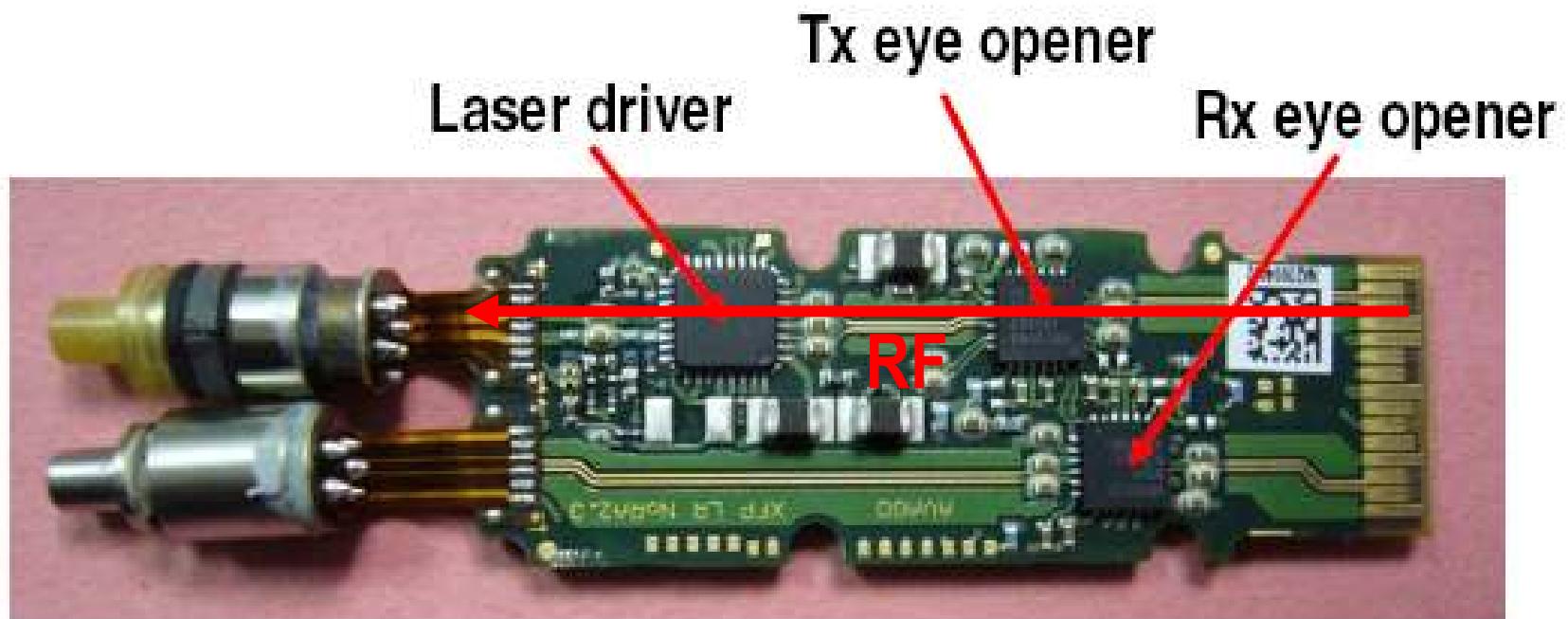
(b)



(c)

Fig. 11. Characteristics of TOSA directly probed at the end of outer leads: (a) measurement scheme, (b) E-O response, and (c) \$S\_{11}\$ return loss.

# Intensity modulation of laser sources: *Package parasitics (Module + TOSA)*

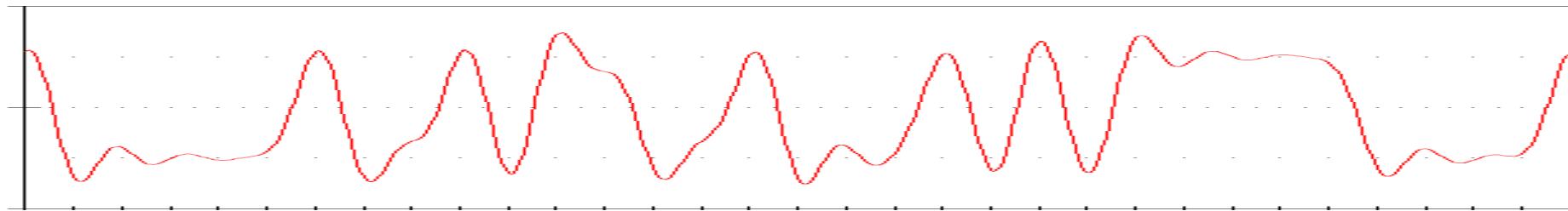
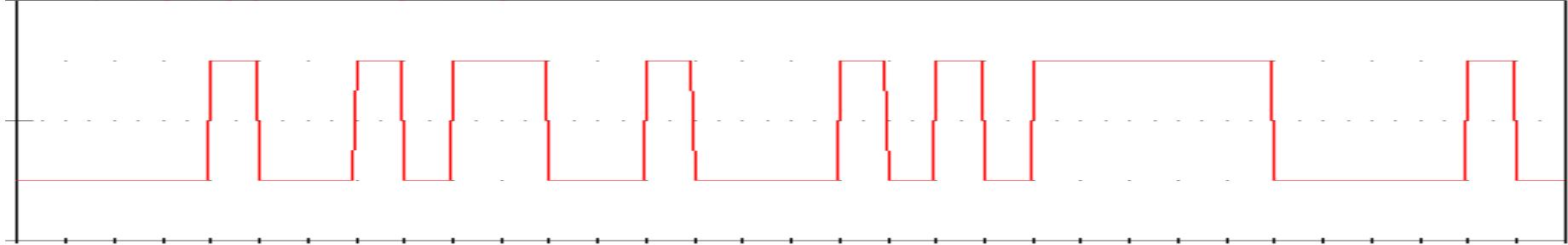


XFP Transceiver, 2005

# Large Signal modulation

*Recalls of digital communications*

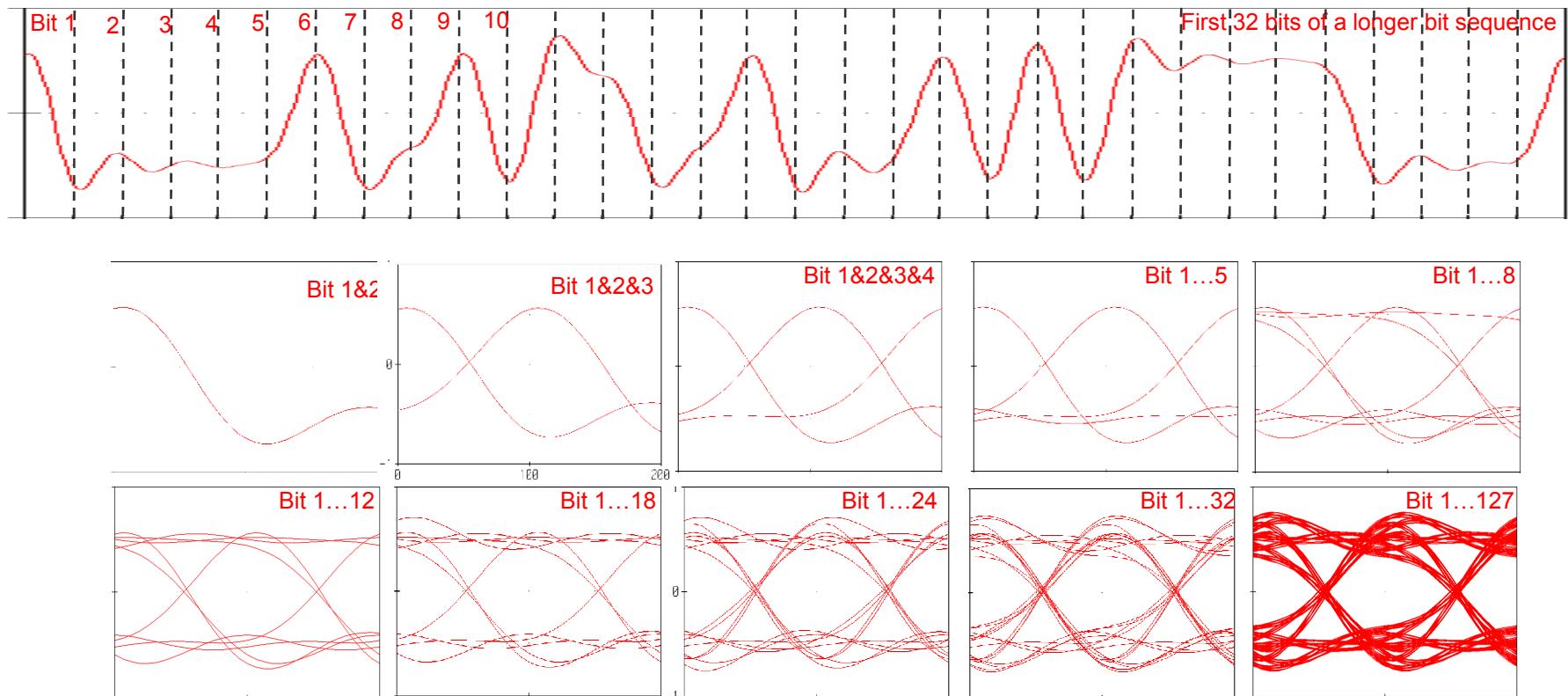
A bit stream like this



can be heavily distorted passing through a non ideal channel;  
bit shape can be broadened and spread out of its time slot,  
overlapping  
on its neighbours : this is called “**InterSymbol Interference (ISI)**”

# Recalls of digital communications (2)

A picture like this gives little information on signal distortion

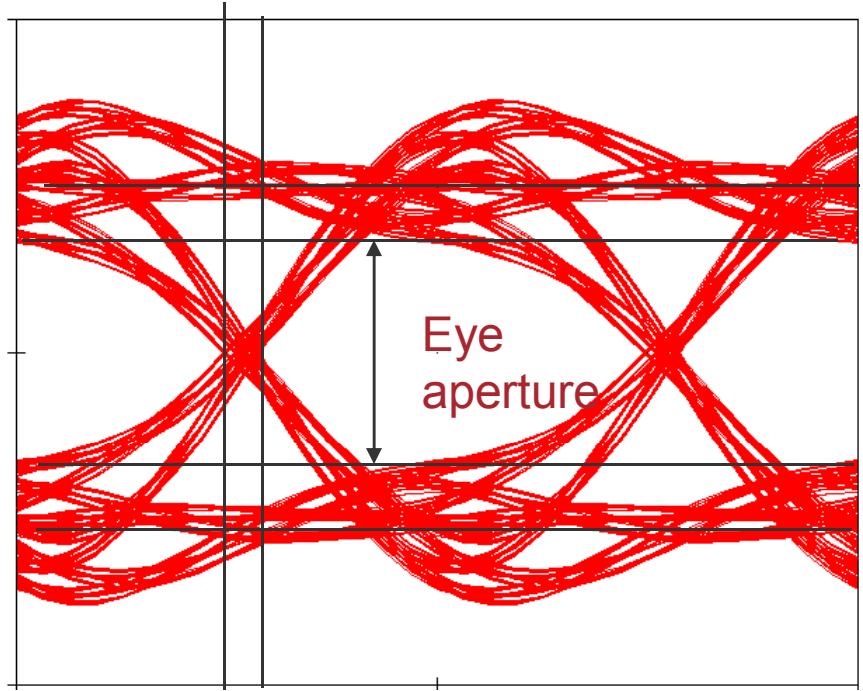


To better evaluate signal distortion an “Eye Diagram” is built

The eye diagram is obtained by slicing the bit sequence in one (or more) bit time slots and overlapping them.

# Main parameters of an eye diagram

simulated

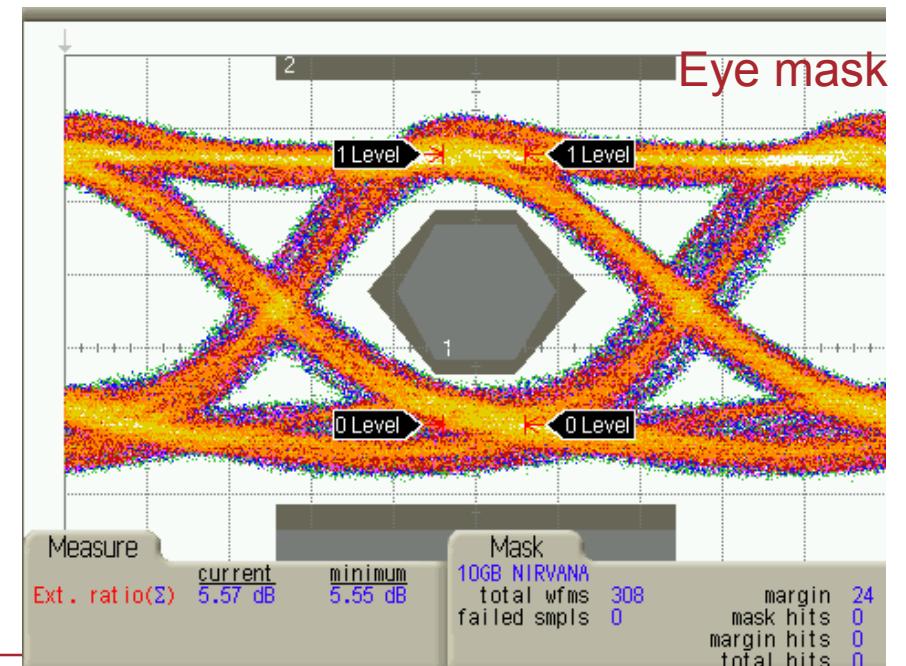


Jitter :

DJ deterministic or pattern dependent jitter

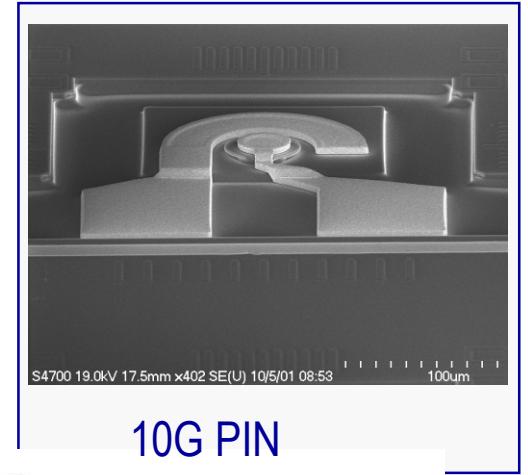
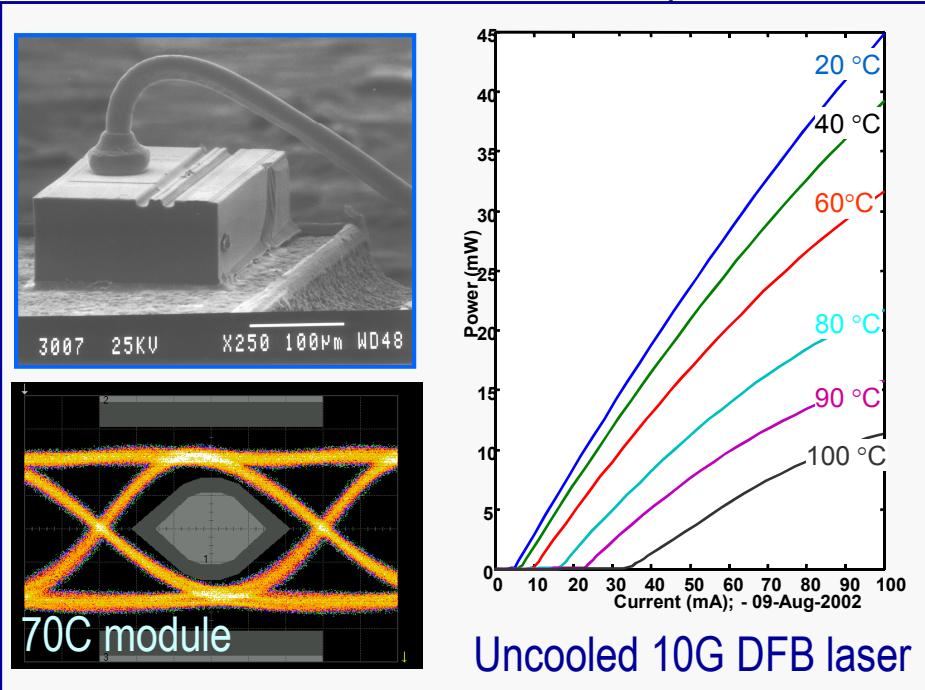
RJ random jitter

experimental



# Agilent uncooled InGaAsP BH 10Gb DFB/PIN for 10GBASE-LR product

- Torino R&D team for Ipswich MFG. First product release: first 10G DFB and first 10G PIN for Xenpak – *first 10G uncooled hot pluggable transceiver in the market*
- DFB uncooled PNIP buried lasers, InGaAsP based



10G PIN



Post deadline at ECOC 2001

# 10 Gb/s uncooled InGaAlAs ridge FP laser

## 20 ° C base chip temperature:

- Threshold 7.6 mA
- High power 23 mW

## 85 ° C base chip temperature:

- threshold 15.6 mA
- power 16.8 mW

## 95 ° C base chip temperature:

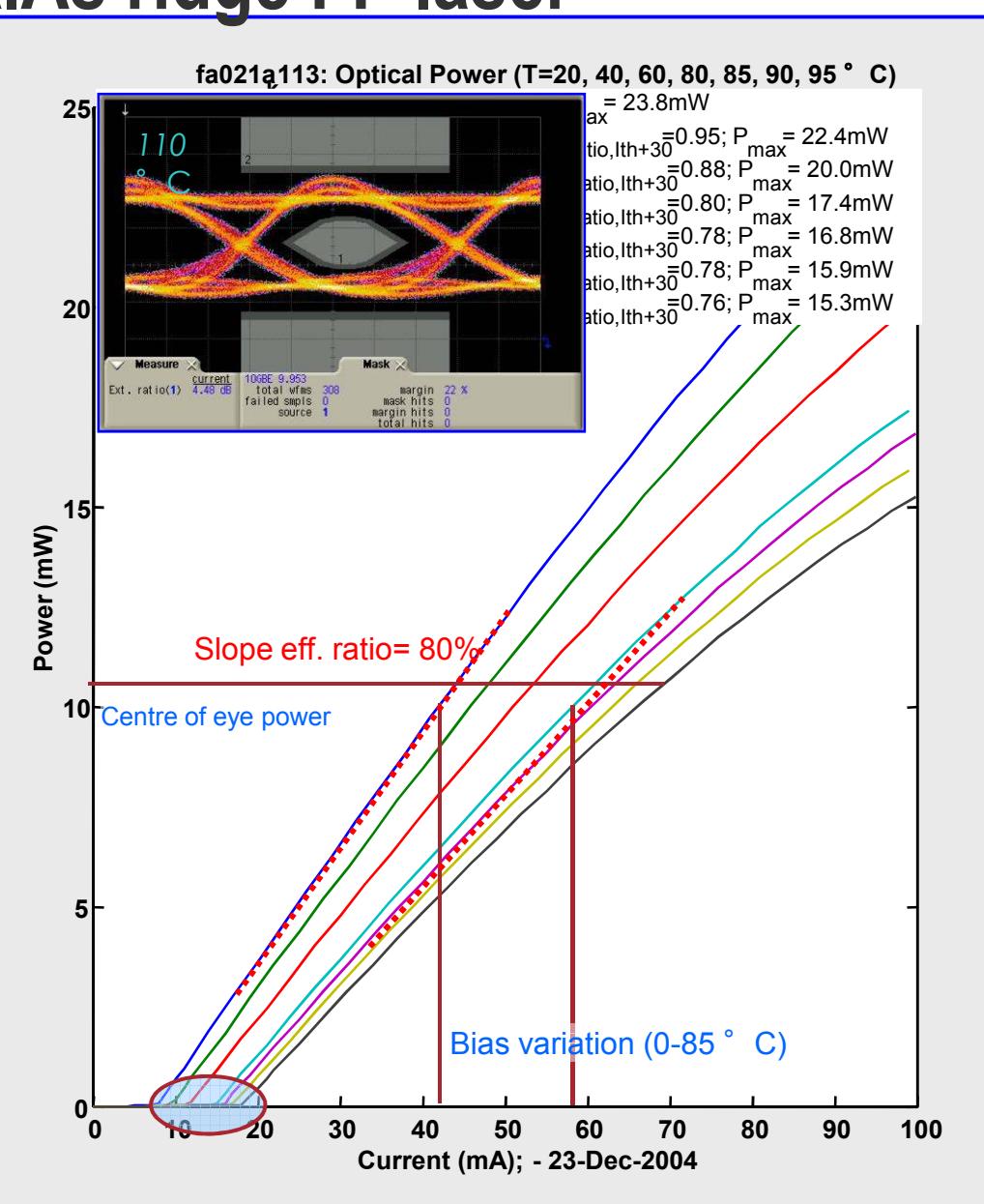
- threshold as low as 18 mA
- Still more than 15 mW

## Key points:

- High optical power enable high coupling loss
- Small threshold increasing up to 95 C since high  $T_0$
- Small bias variation over T
- Small efficiency degradation over T

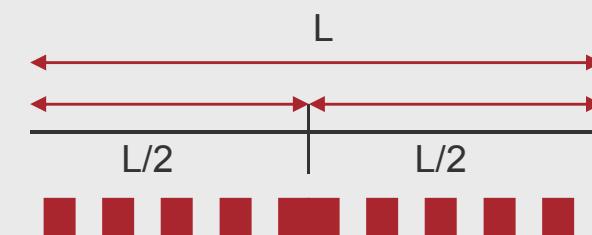
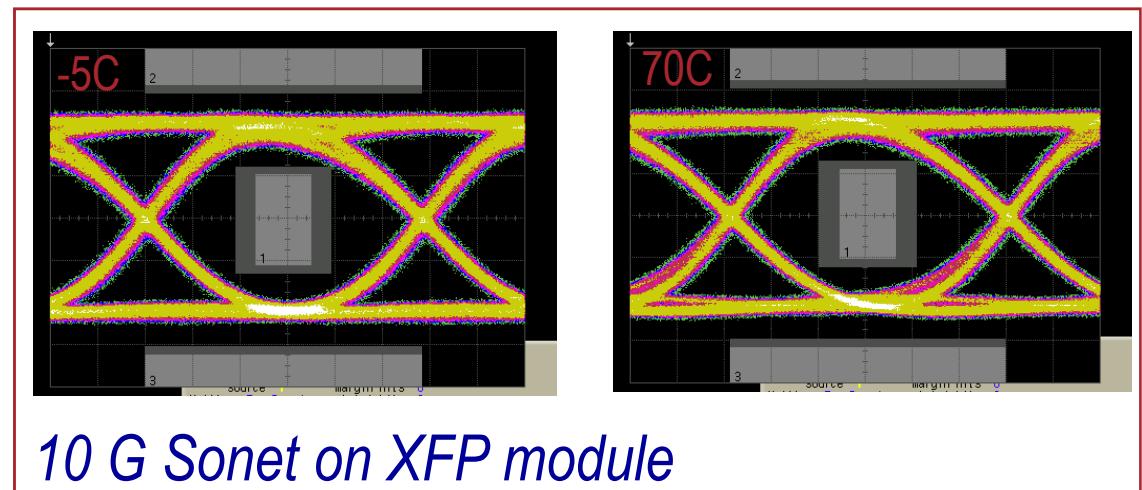
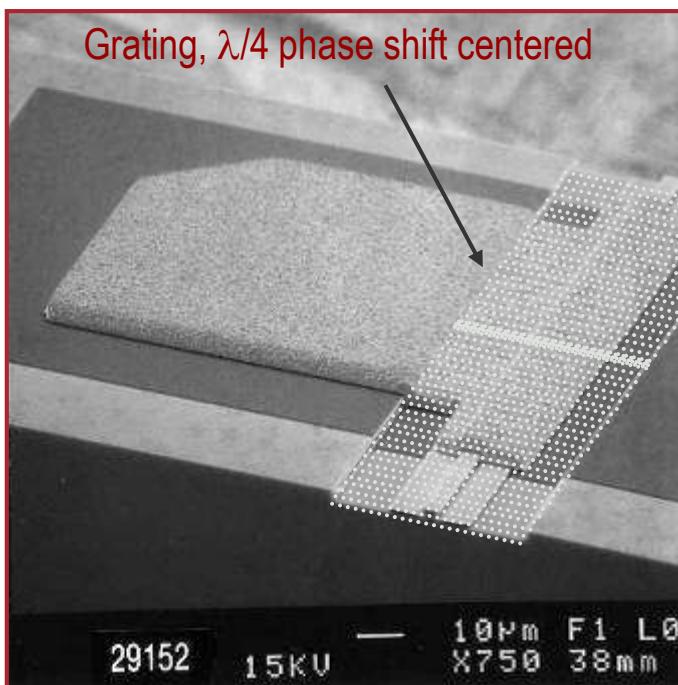
⇒ Constant eye quality with constant modulation current!

Paoletti et al, Post deadline at OFC 2005

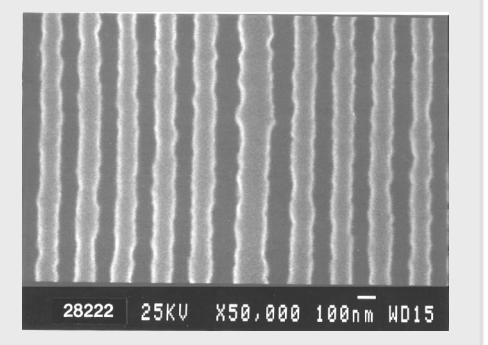


# OC48 (4CG4), 10GbE (4CG5), 10Gb Sonet (4CG3)

*Uncooled DFB Laser for XFP, SFP and SFP+ platform (2005 – 2006)*

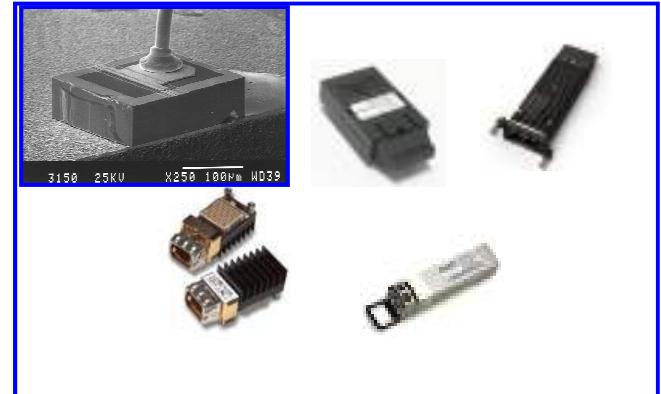


Phase shifted grating



# Semiconductor lasers for optical communication

- Laser sources for “*pluggable transceiver world*”
  - *Design for performances*
  - *Fast lasers*
- Transceiver for next generation networks
- *Torino Technology Center - Avago Technologies Italy*



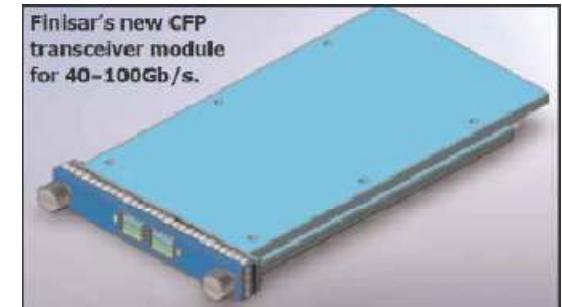
# What next?

## 40 and 100 Gb/s Ethernet, 16-32Gb FC standards

- for 40Gb/s
  - 40GBASE – SR4, 850nm, 4 x 10GbE; **40GBASE – LR4, 1300nm, 4 x 10GbE CWDM**
- for 100 Gb/s
  - 100GBASE – SR10, 850 nm, 10 x 10GbE; **100GBASE – LR4, 1300 nm, 4 x 25GbE, LAN WDM 4.5 nm spaced or PSM4 (4 single mode fiber for short reach driven by datacenter)**
- **16G FC – 32G FC standard for Fiber channel**
- **Standard and MSA have focused the technology development:**
- 16G FC transceiver SFP+ commercially available
- First 40Gb/s and 100Gb/s CFP MSA ...*but form factor is the key development*



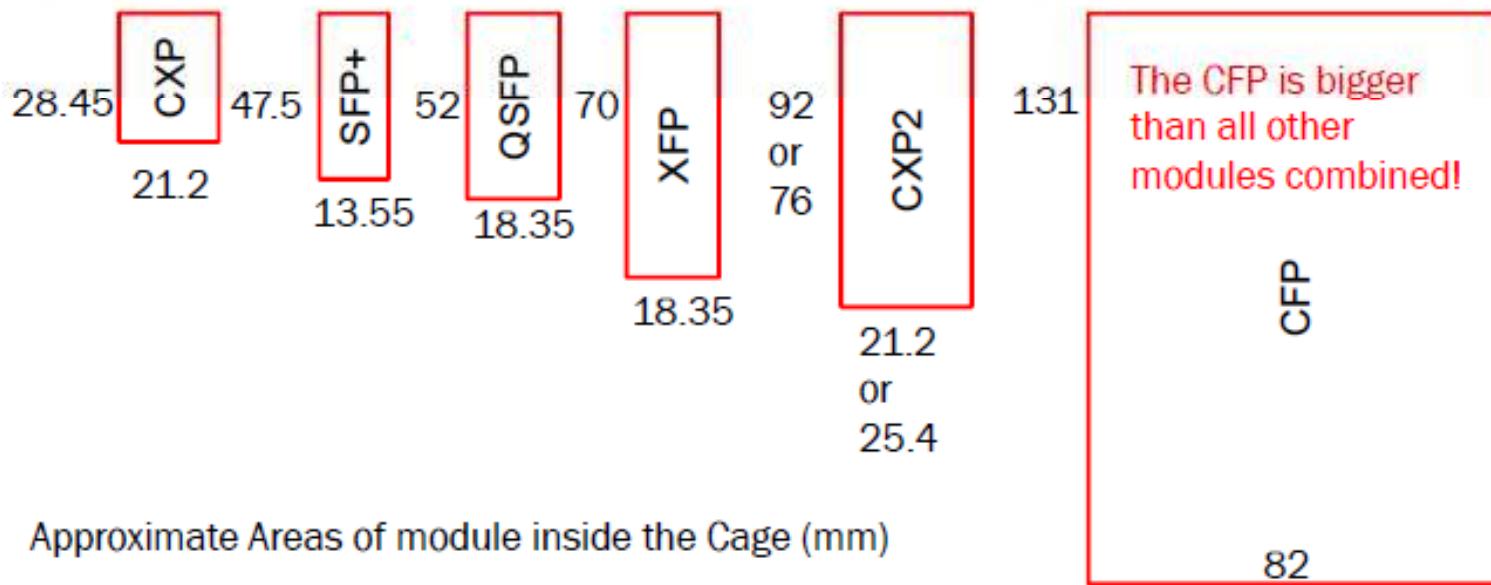
Opnext's 16G Fiber Channel SFP+ module.



OFC 2009-2010

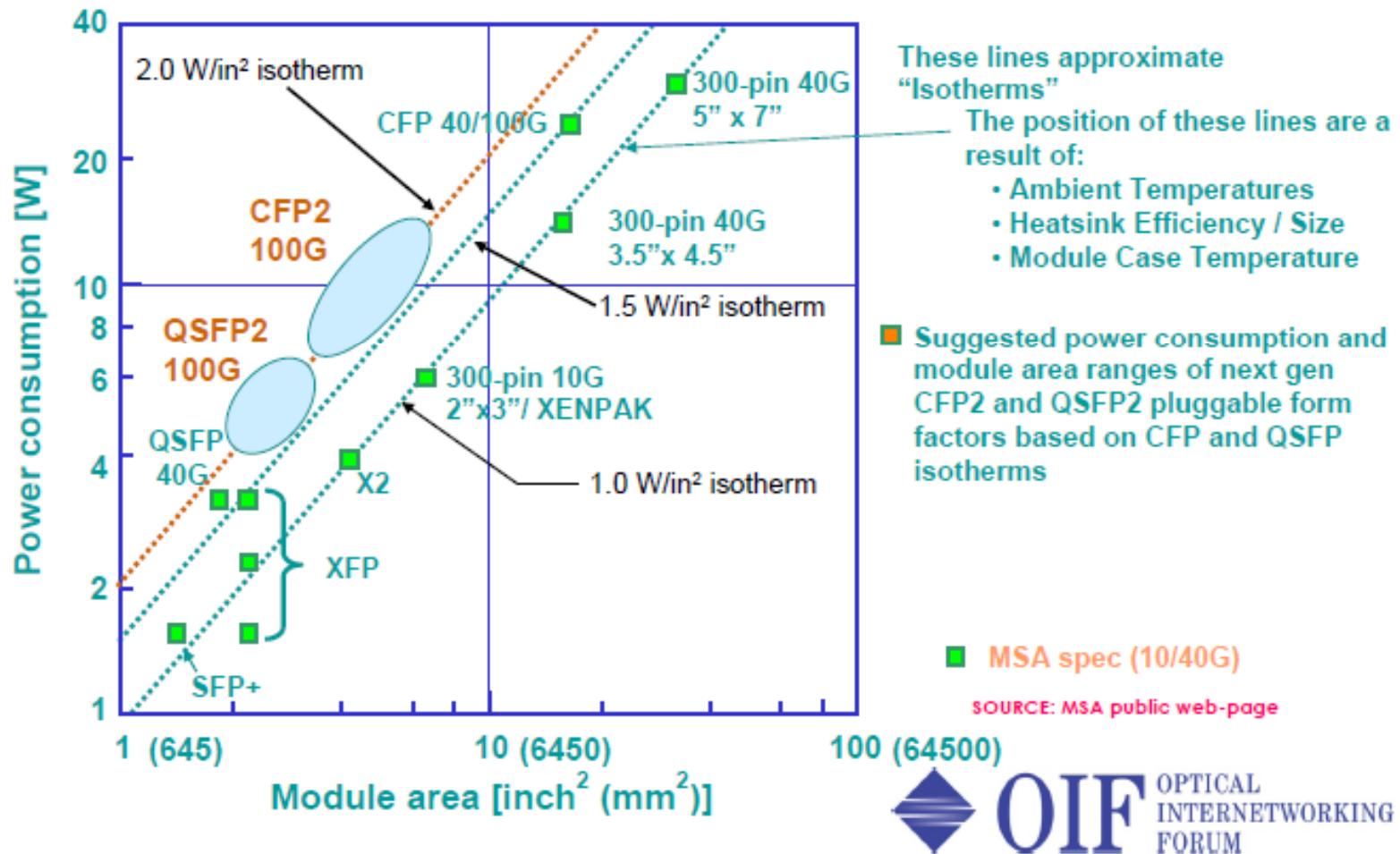
# Area and Power Dissipation: the competition on optical modules

Module	CXP	SFP+	QSFP	XFP	CXP2	CFP
Area (sq in)	0.9	1.0	1.45	2.0	3.0	16.45
Max Power (Watts)	1	1.5	3.5	3.5	6	24/32



# Next Gen 100G SMF Optical Module

*Power Dissipation: data center driving force toward low power dissipation*



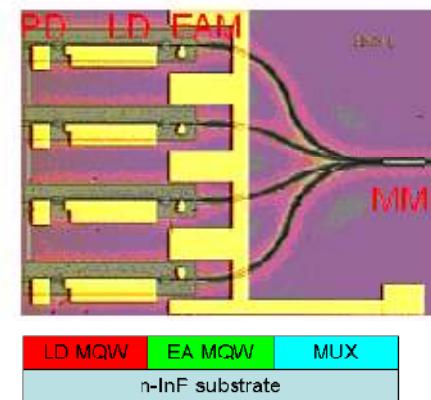
# Sources for 100Gb:

**4 × 25-Gbit/s, 1.3-um, Monolithically Integrated Light source**

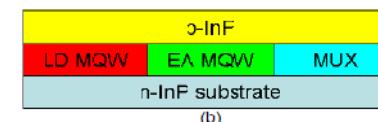
*Takeshi Fujisawa (NTT Corporation, Japan)*

- Application: 100GbaseLR4 and ER4 (10 and 40 km) 1300nm
- Now CFP with 4 TOSAs, WDM filter
- To move from CFP to smaller size (CFP2/?):
  - integration
  - Low power consumption
- Then NTT approach
  - Monolithic integration of EADFB and MUX (MMI)
  - $2 \times 2.6 \text{ mm}^2$
  - Quarter wavelength shift DFB
  - Ridge, buried in BCB
  - Shallow ridge EADFB, deep ridge MUX
  - InGaAlAs
  - Double “butt join” (one also fro the low doping cladding in the MMI...)

**Complicated/high cost/high power dissipation**



(a)  
LD MQW EA MQW MUX  
n-InP substrate



(b)  
o-InP  
LD MQW EA MQW MUX  
n-InP substrate

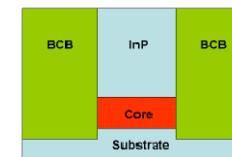
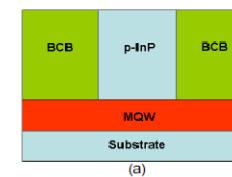
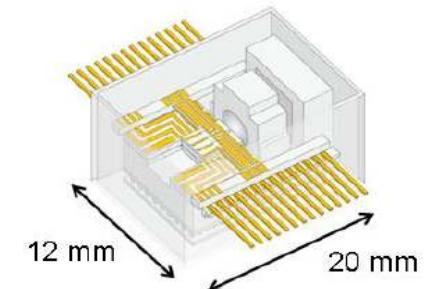


Fig. 4: Cross sections of (a) shallow- and (b) deep-ridge waveguides.



12 mm 20 mm

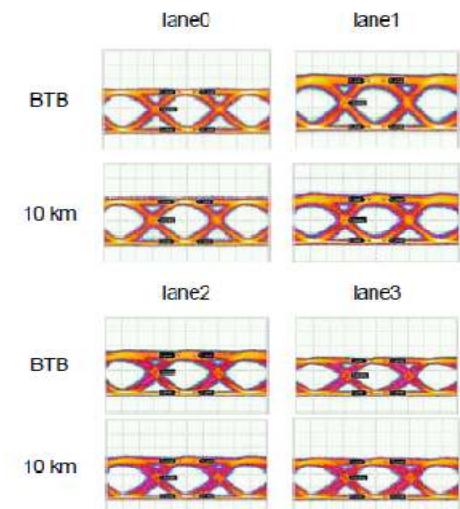


Fig. 14: 25-Gbit/s eye diagrams (simultaneous operation).

# Sources for 100Gb:

*DFB technology: best as cost and power dissipation....*

OFC 2007 session: Uncooled and semicooled DFB laser sources at 25 and 40 Gb/s

- Avago: best eye quality up to 70C, 25Gb/s



Paoletti et al, OFC 2007

R. Paoletti, 11/2011

**AVAGO**  
TECHNOLOGIES

# Next steps: revolution on active material?

## *Is Quantum Dot ready to go?*

**OFC2009, OWJ1, “High-Speed and Temperature-Insensitive Operation in 1.3- $\mu\text{m}$  InAs/GaAs High-Density Quantum Dot Lasers”, Fujitsu**

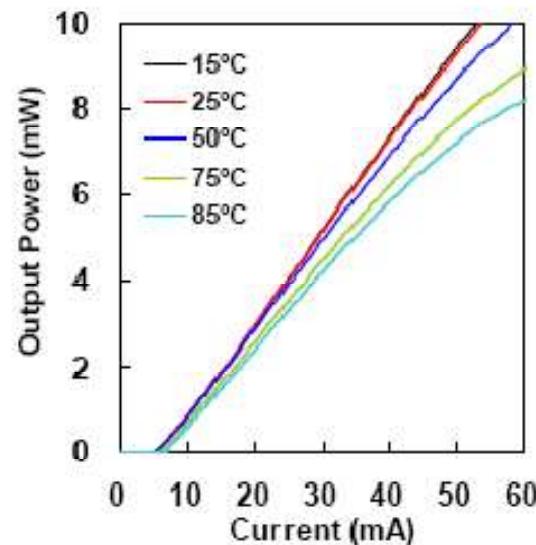


Fig. 3 Light-current characteristics of the fabricated laser

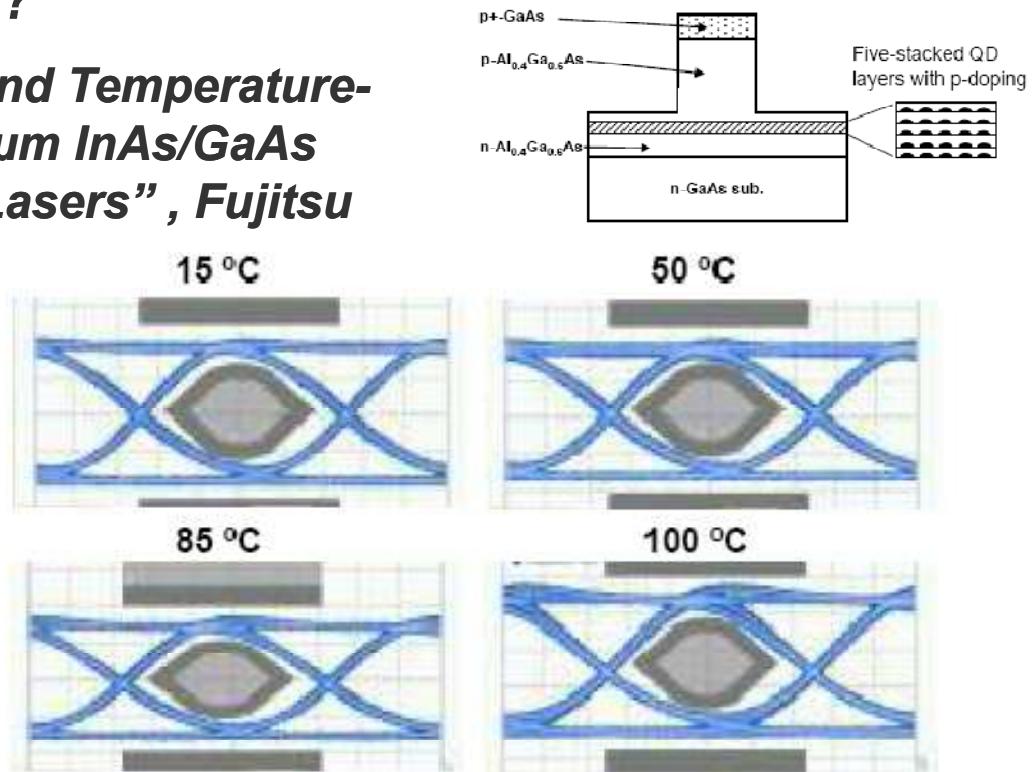


Fig. 4 10.3-Gb/s filtered-eye-diagrams in the fixed driving condition at 15, 50, 85, and 100 °C. The mask margin of more than 48 % was maintained at all temperatures.

200 um long 1.3um ridge FP laser, with amazing performances... on GaAs . Announced to be “*ready for production*”....

# ... Or real revolution will be Silicon Photonics?



## Silicon light emission – How?

- Bulk silicon
- Low dimension Silicon
  - Silicon nanocrystal (Pavesi, ...)
  - Periodic nanopatterned crystalline silicon (Jimmy Xu)
- Er dopants (Dal Negro,...)
- Avoid direct interband transition
  - Raman laser (UCLA/Intel)
- Another material for gain (hybrid approach)
  - Epitaxial
    - Ge
    - Quantum Dot
    - Pillars
  - Bonding
    - Dice level
    - Wafer level (BCB or Molecular)

ECOC 2010, John Bowers, Dept of Electrical and Computer Engineering, UCSB

# Silicon Photonics

## EPI: Ge on Silicon

### Ge-on-Si High Efficiency Photonic Devices

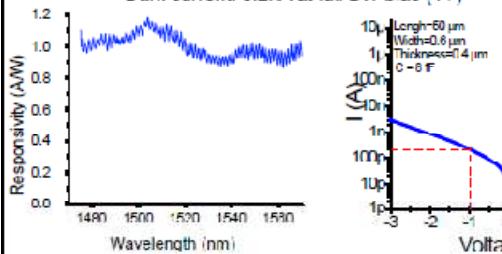
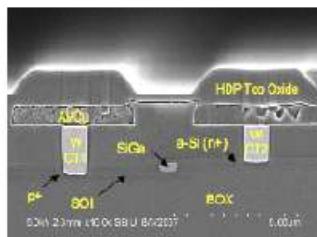
#### Low Power Consumption Ge-Si Photodetector

##### Waveguide integration in CMOS:

- Transit time decoupled from RC
- Independent absorption length
- Small Size: 600nm x 50  $\mu\text{m}$

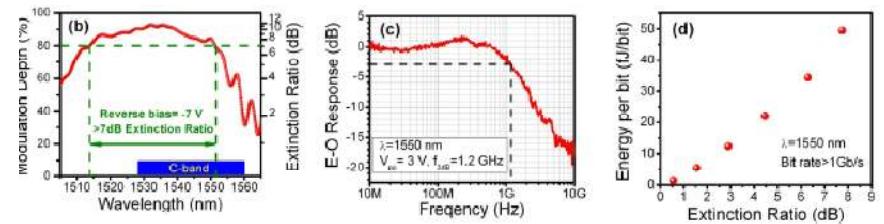
##### Performance:

- $\text{RC}_{\text{device}} = 12 \text{ ps}$
- Capacitance = 8 fF
- Responsivity >1 A/W at full BW
- Flat responsivity from 1470-1570 nm
- Dark current: 0.2nA at full BW bias (1V)



### Ge-on-Si High Efficiency Photonic Devices

#### GeSi EA Modulators – Lowest Energy & Smallest Footprint



##### Waveguide integration in CMOS:

- Field-modulation by Franz-Keldysh effect
- Same process and mask level as photodetector

##### Performance:

- >7 dB extinction ratio from 1510-1552 nm
- 1.2 GHz bandwidth for 2 Gb/s digital photonic interconnects; ~100 GHz expected
- 25 fJ/bit; low capacitance (11 fF); and low dynamic drive voltage ( $V_{\text{pp}}=3\text{V}$ )
- Modulation depth pseudo-linear with voltage at 30%/V (CC=0.997).

*State-of-the-art performances by Ge on Silicon on detectors, improving on modulators*

ECOC 2010, Lionel C. Kimerling, MIT

R. Paoletti, 11/2011

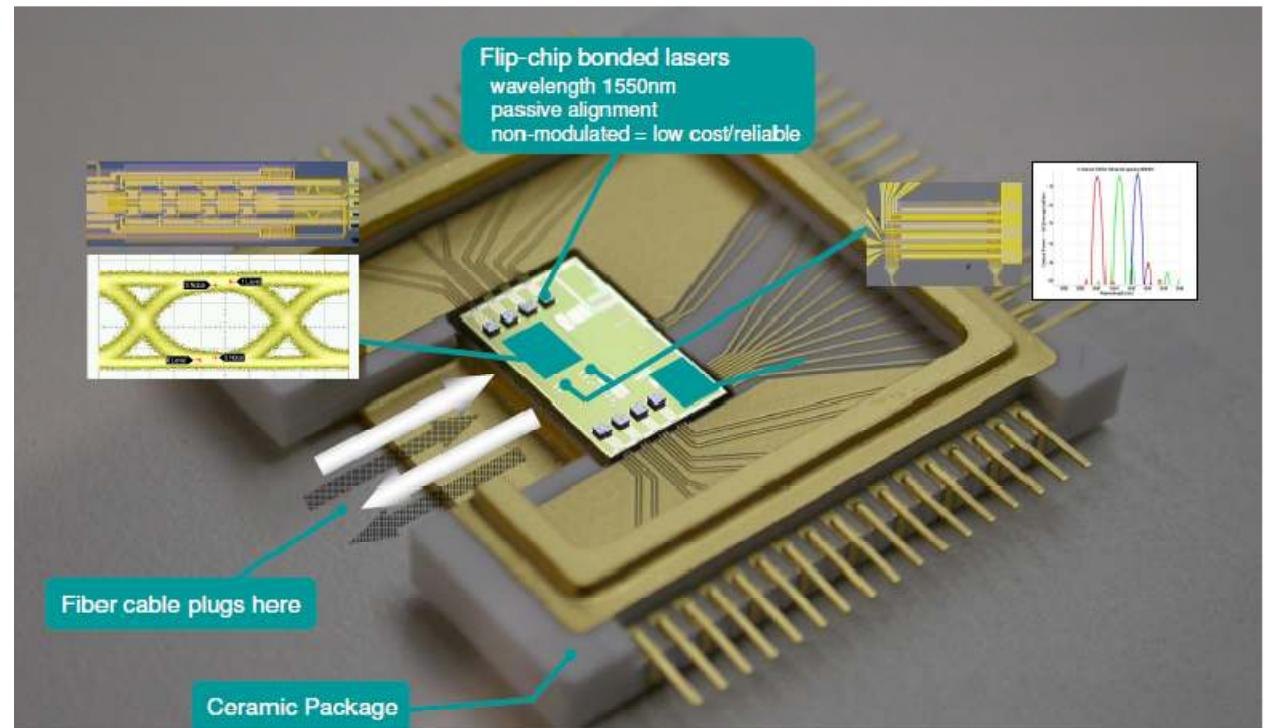
**Avago**  
TECHNOLOGIES

# Silicon Photonics;

## *Hybrid approach: die level*

III-V material for gain (hybrid approach), Si for waveguides and modulators

- Bonding: Die level
  - **Flip-chip (Luxtera)**

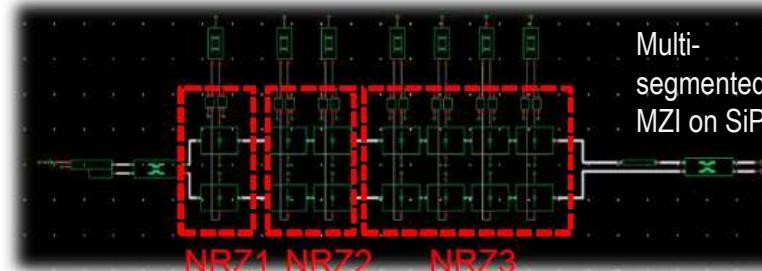


*Taking the best from III-V and Si world... Smart guys! Promising solution for advanced modulation format and parallel approach (PSM4)*

# And electronics can boost optics to higher datarates!

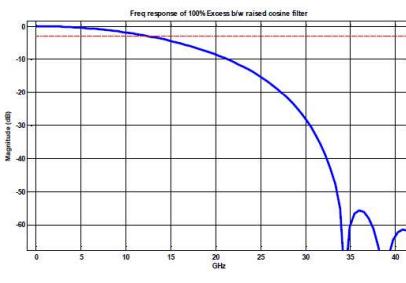
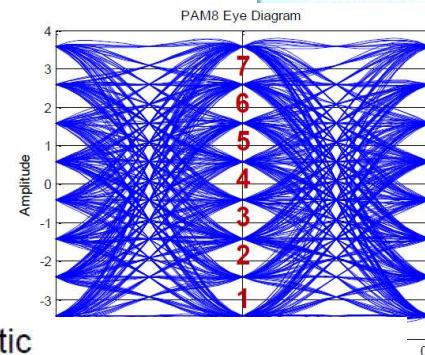
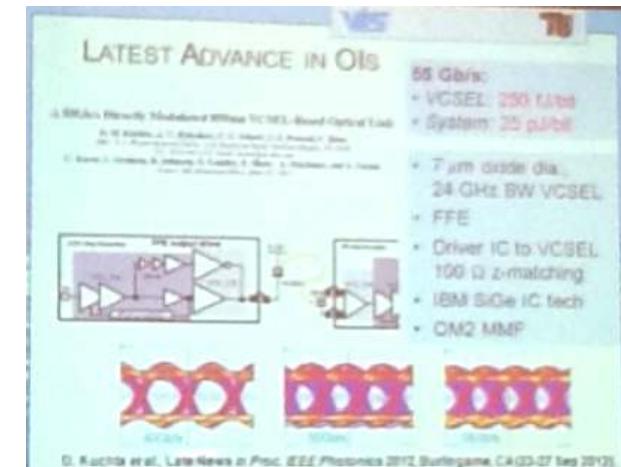
- Using pre-emphasys: 25 Gb VCSEL, 44 Gb using FFE at driver and good electrical matching... (ISLC 2012)
- Using Multilevel coding (IEEE 802 committee)

Opto-electronic Schematic



- Or using FEC

- limiting to  $10^{-5}$  BER and allowing low cost optics: power budget, reflection sensitivity, etc...



	Ethernet rate
PAM-2	100.39 Gs/s
PAM-4	50.20 Gs/s
PAM-8	33.46 Gs/s
PAM-16	25.10 Gs/s
PAM-32	20.08 Gs/s



# Avago Technologies Italy

Acquisition by Agilent Technologies 19 April 2000

Former technology dept. of CSELT; Today XX Eng YY OPer.

Activity: **R&D and Production (III-V Team)**

- Short term Development projects (transceivers @ 10 Gbit/s and higher)
- Medium term Research projects for active and passive devices
- Development and Production of 10G FP/DFB/EML laser source

Activity: **Transceiver R&D (Product Team)**

- Design of next generation single mode transceiver

Facilities (III-V team)

- 1350 m<sup>2</sup> of clean room: class 10-10000 (plus R&D Lab, offices).
- EPI (2 MOCVD), material characterization, processing (including EBL), die fab (singulation, coating, testing, assembly and reliability tests)

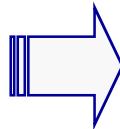
Expertise: **optoelectronic and photonic technologies**

- New transceiver, devices and components conception and design
- Semiconductors
- Device design, prototyping and characterisation

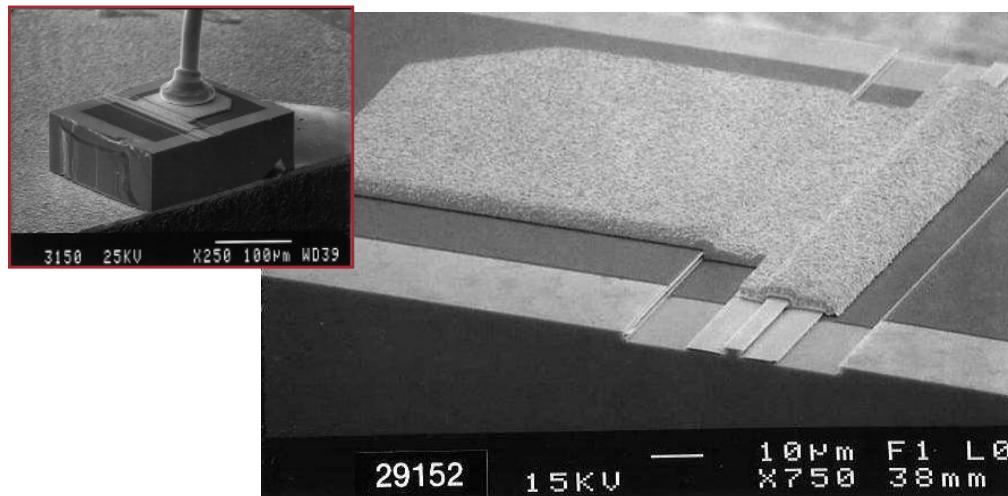
# Technology platform for high yield manufacturing

*established from 2003 on*

- *high yield*
- *easy to manufacture*
- *high performance*

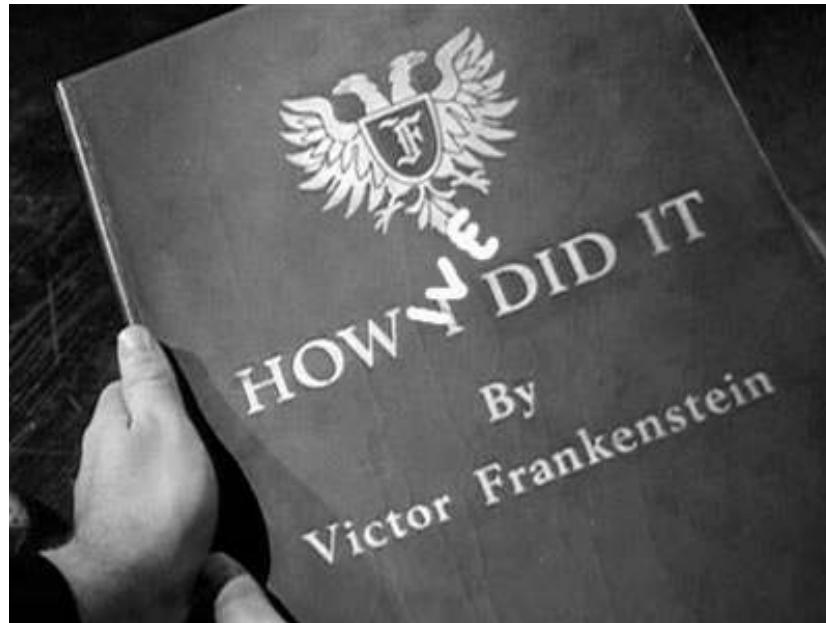


- Aluminum based MQW material
- Superior high T performances
- Ridge waveguide
- High yield; compatible with Al MQW material
- Quarter wavelength grating
- 100% SMSR yield



*Proven reliability, with > 50 M devices x hours in 3 years production*

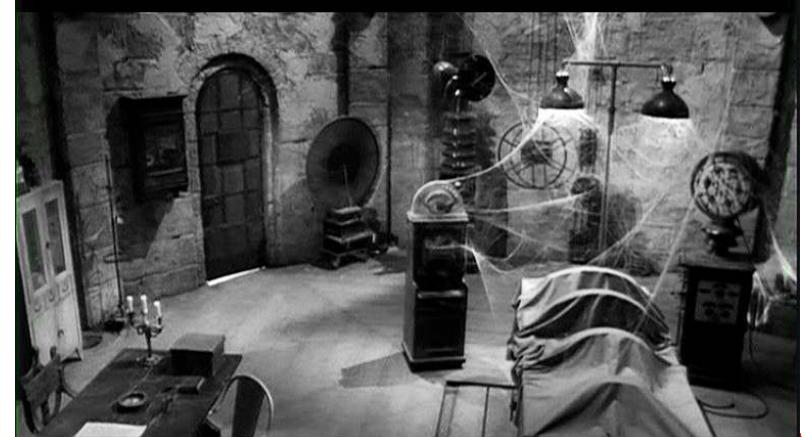
# How we did it.....The III-V Technology in Turin



.. advanced lasers? A teamwork ..



...advanced technologies!

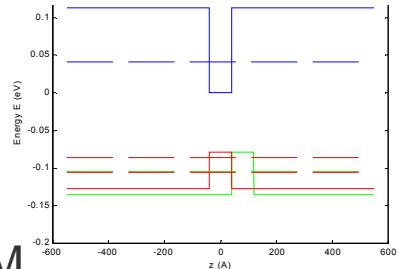


# How we did it.....

## (1) Design/Modeling

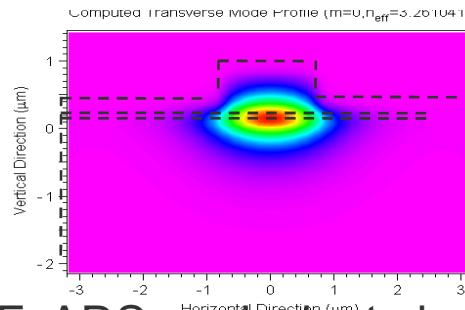
### 1. Material properties (Q.M.)

#### MQW band profile and levels

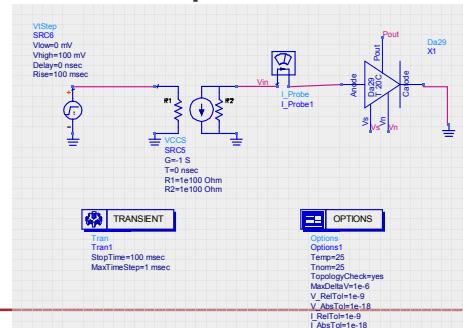


### 1. E.M.

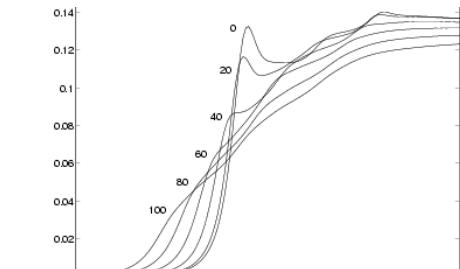
#### Waveguiding properties



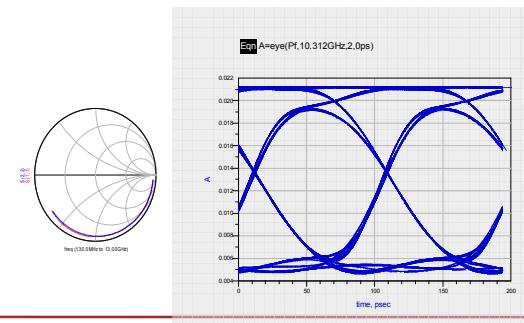
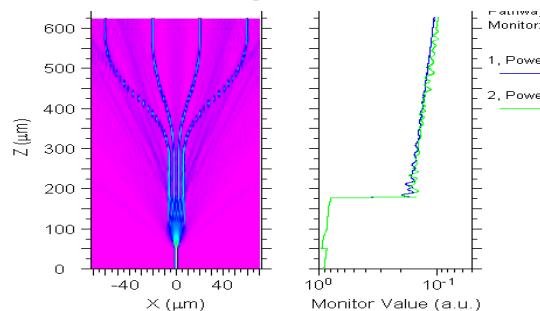
### 2. RF: ADS equivalent circuit



#### Optical properties: $n+ik$ (I, F, T)



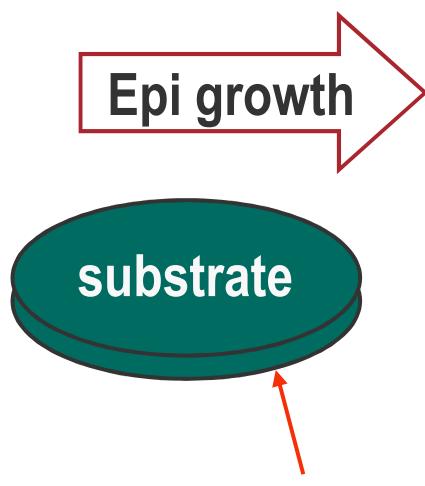
#### Beam Propagation Method



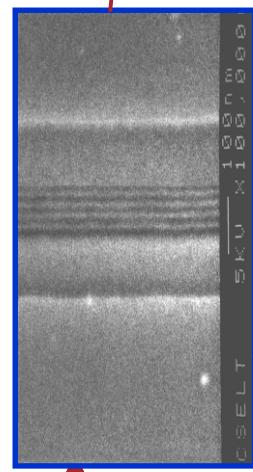
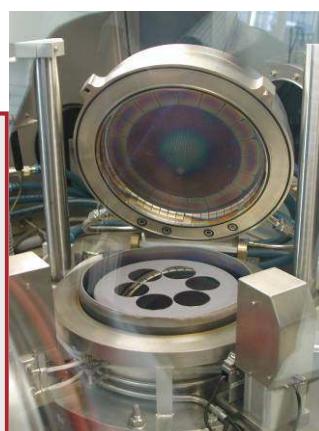
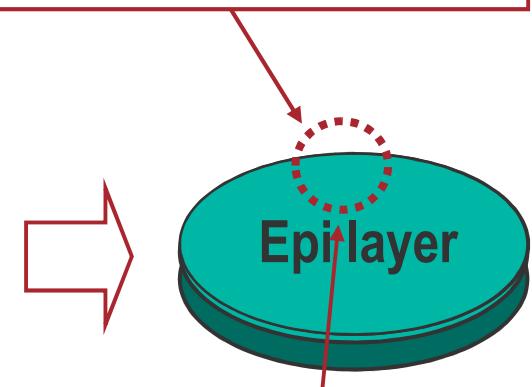
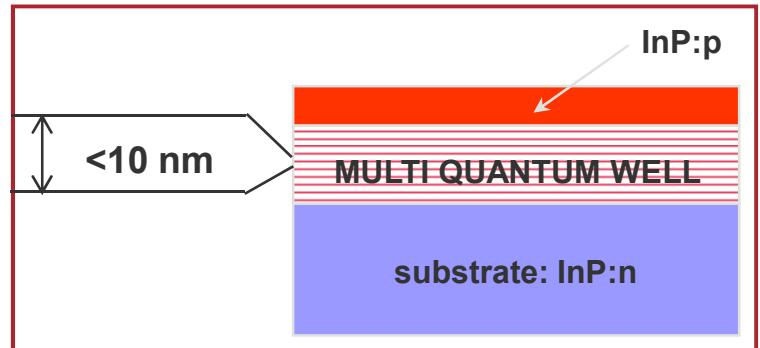
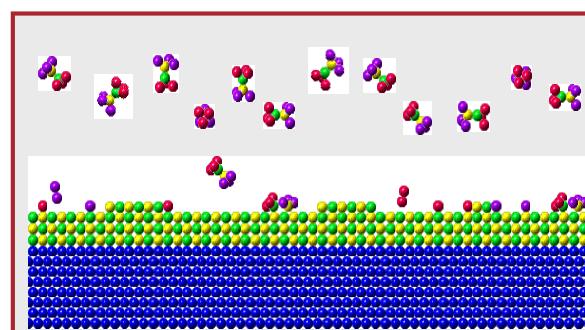
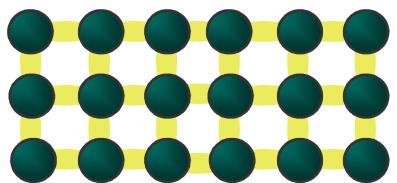
R. Paoletti, 11/2011

# How we did it.....

## (2) Epitaxial growth



MOCVD reactor



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TECHNOLOGIES

# ⇒ How we did it.....

## (3) Material characterization



X-Ray diffraction: crystal quality +composition



Photoluminescence: alloy composition



Scanning Electron Microscope (SEM)

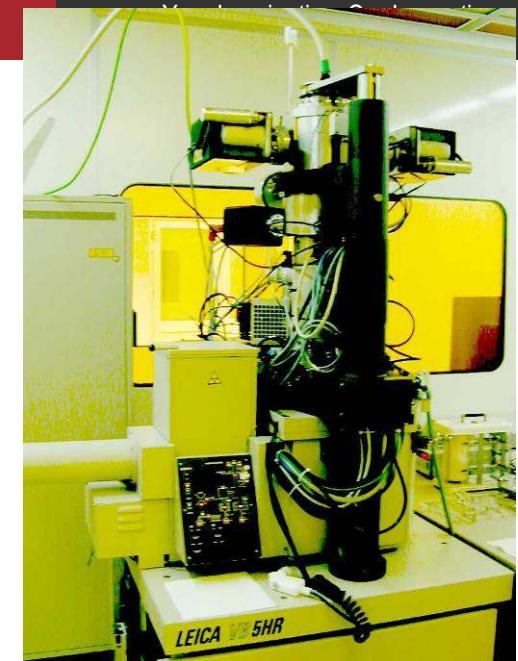
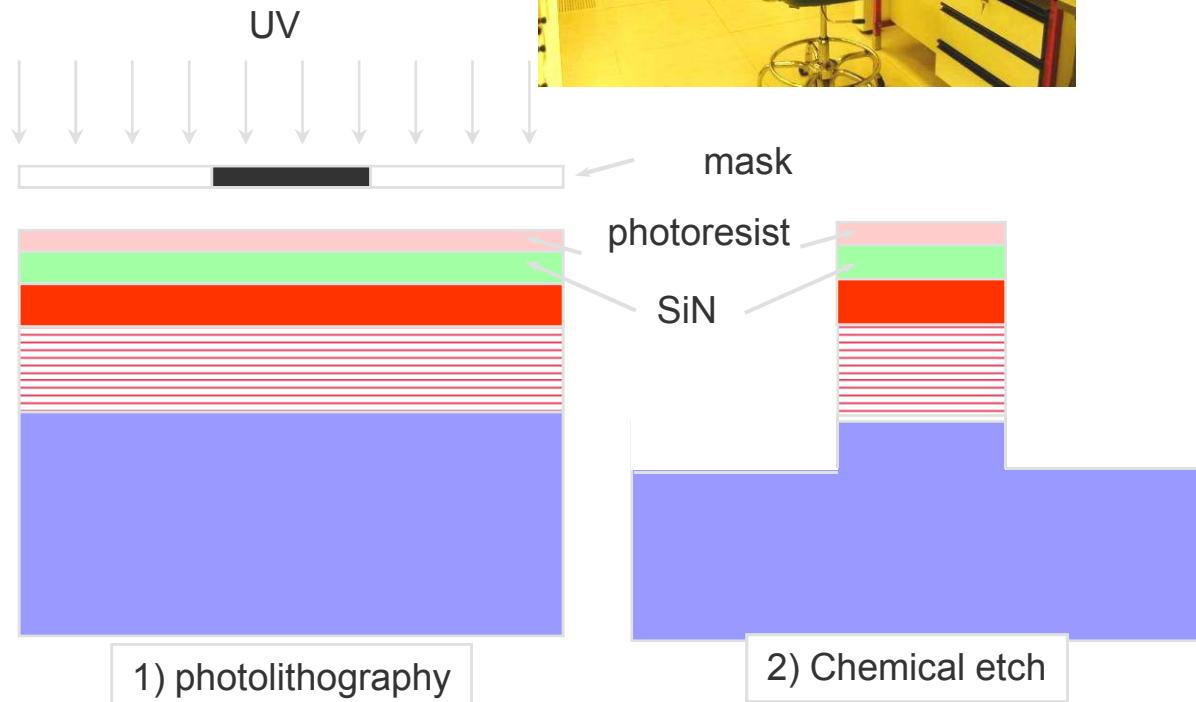


C-V profilers: doping profile

# How we did it.....

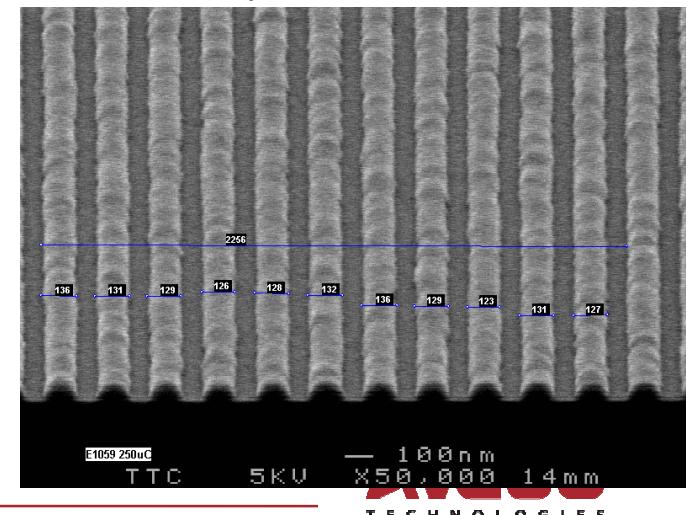
## (4) Processing

### Photolithography



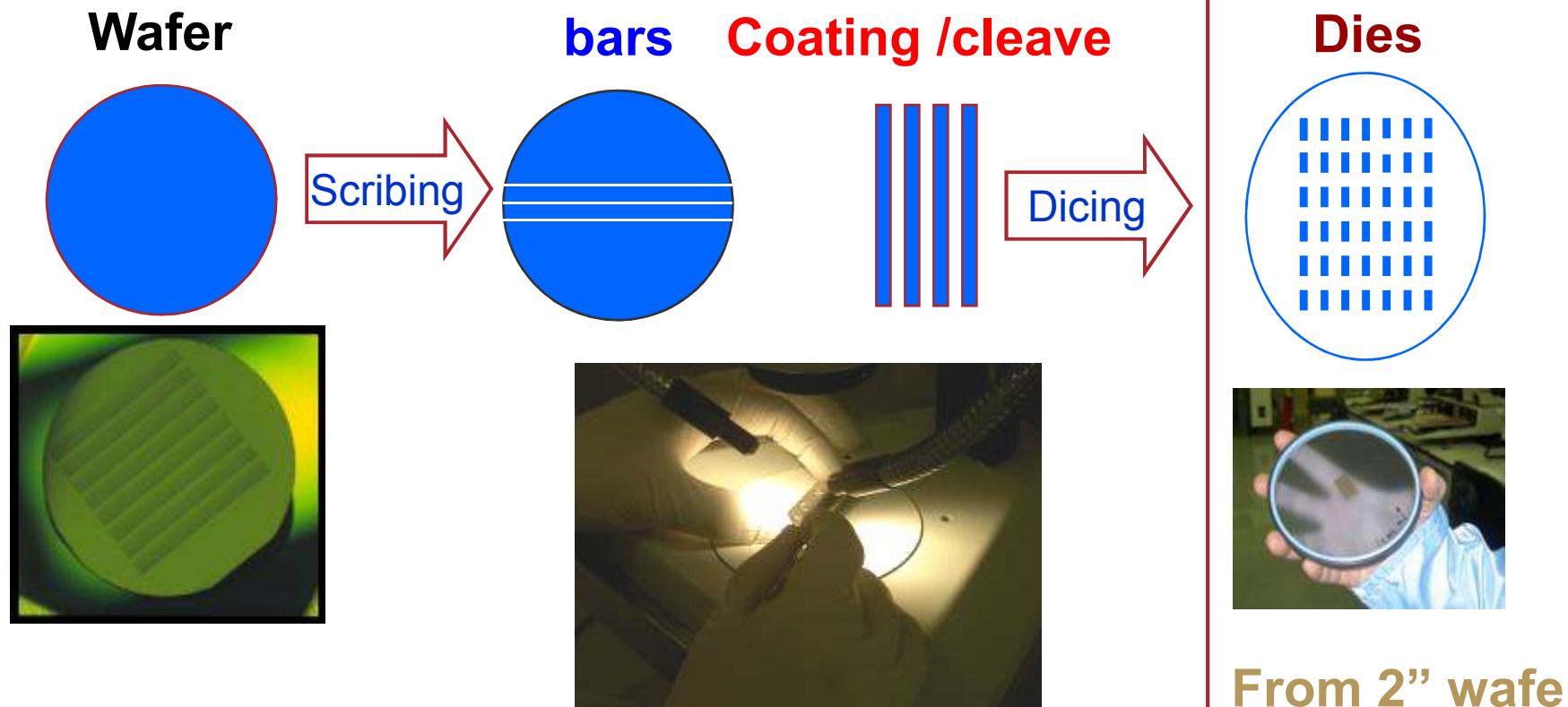
### Electron Beam Lithography

- ✓ 70 nm line in 75 nm thick resist
- ✓ 200 nm pitch lines



# How we did it.....

## (5) Scribing: from wafer to chip



# How we did it.....

## (6) Automatic testing

### What are LDIs?

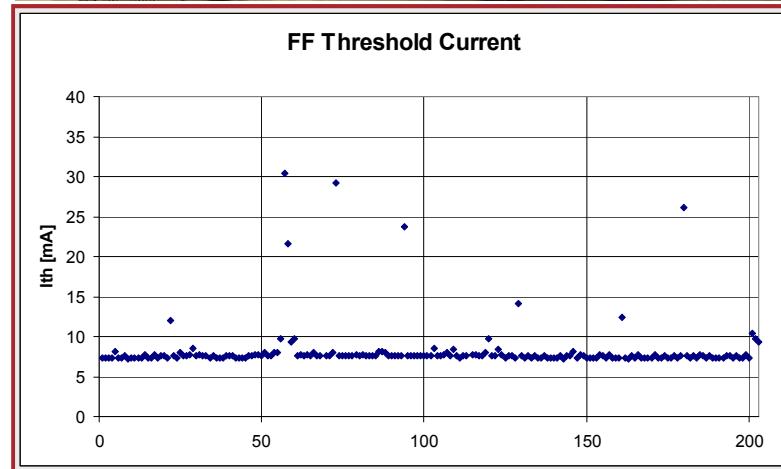
Laser Device Inspectors are automatic systems for 100% device testing and screenings.

### System capabilities and scope:

- Test: pulsed measurements on chip @ R.T.:
- F/B LIV, spectrum, rev. leakage, chip size and tilt
- 10G FP, 10G DFB, EML



MOV001

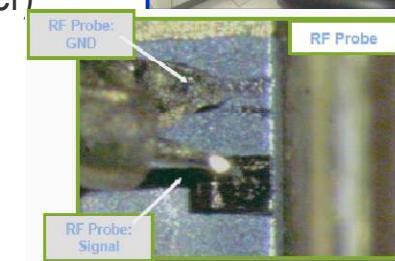
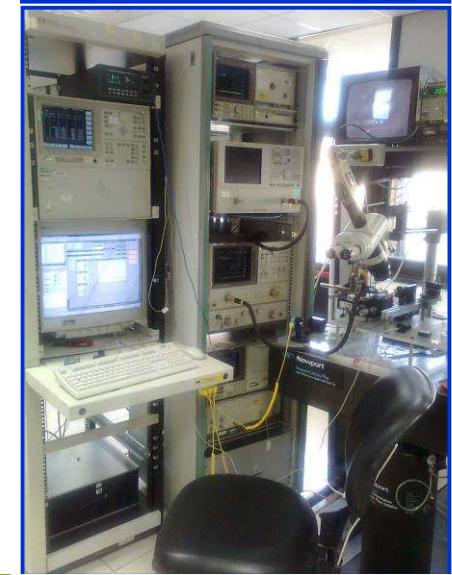


Statistics of main parameters

# How we did it.....

## (7) R&D lab characterizations (new products dev.)

- Dedicated area (130m<sup>2</sup>), large set of characterization techniques
- Measurement benches for:
  - FP and DFB lasers; Multi-electrodes (EML, Tunable) lasers
- Static measurements on tile (10 - 100 C) and Headers
  - F/B LIV, spectrum, low current, rev. leakage, Far Field, ...
- Dynamic characterization: “directly on chip” probing (10 - 100 C)
  - Small signal S<sub>21</sub>, S<sub>11</sub>, parasitics and active dynamics up to 20 GHz
  - Large signal dynamic characterization:
    - Pattern generators at 1-12 Gb/s and 4-60 Gb/s (SHF); up to 32GFC complete eye diagram measurement set-up (including optical receiver)
    - Up to 12 Gb/s BERT test (200 km fiber)
- ...plus standard production testing / validation line
  - LDI for screening, statistic and process debug purposes
  - Stress tests (BI/ESD/ALT) for reliability assessment and qualification



**Key points:**

- RF Probes;
- Accurate calibration

# From R&D to production

## *Developing a reliable technology....*

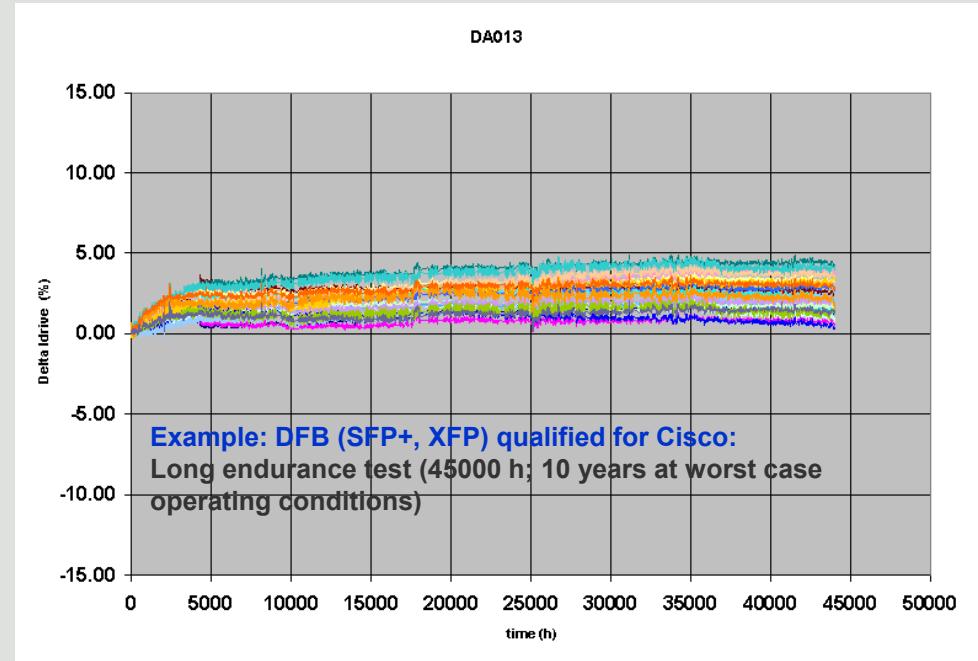
- Reliability has always been the key strength in a III-V world
- Customer reliability expectation is almost compared to the ‘telecom’ field, *but for low cost – consumer products*

⇒ **Reliability is the key investment in the III-V area**

### DFB (SFP+, XFP) qualified for Cisco:

- many million devices\* hours
- Long endurance test

*Enormous investments...*



# From R&D to production

## *Testing a production volume....*

- Testing is one of the most expensive part in the III-V production, which require 100% testing of laser chip!
- Only key team have testing capability suitable for mass-production (not for start up..)

→ *R&D design for Testing*



R&D Avago  
VCSEL  
Tester: 1  
sec/die



R&D Avago DFB Tester: 20 sec/die



# The end!

## Books

- Ramo Winnery Van Duzer, "Fields and waves in communication electronics", John Wiley.,
- G. Guekos, *Photonic Devices*, Springer, 1999, ISBN 3-540-64318-4
- L. A. Coldren, S. W. Corzine, "Diode lasers and photonic integrated circuits", John Wiley and sons, inc.,
- P. Vasil'ev, "Ultrafast diode laser", Artec House Boston-London
- K. Petermann, "Laser Diode Modulation" and Noise, Dordrecht, The Netherlands: Kluwer Academic Publishers

## Application Notes

- Application Note 1550-6, HP
- Application Note 1287-1
- Network Analyzer Basics
- The Art of Measuring 40G Eye Patterns

## Related published paper

- F. Delpiano, R. Paoletti, P. Audagnotto and R. Puleo, "High Frequency Modelling and Characterisation of High Performance DFB Laser Modules", *IEEE Transaction on Components, Hybrids, and Manufacturing Technology*, Part B, Vol. 17, No 3, pp. 412-417, august 1994.
- R. Paoletti, D. Bertone, A. Bricconi, R. Fang, L. Greborio, G. Magnetti, M. Meliga, "Comparison of Optical and Electrical Modulation Bandwidths in three different 1.55  $\mu\text{m}$  InGaAsP Buried Laser Structures", *SPIE'S International Symposia - Photonics West '96*, pp. 296-305, 30 Jan. - 1 Febr. 1996, S. José, CA, USA.
- R. Paoletti, M. Meliga, I. Montrosset, "Optical Modulation Technique for Carrier Lifetime Measurement in Semiconductor Lasers", *IEEE Photonics Technology Letters*, Vol. 8, No. 11, pp. 1447-1449, November 1996.
- R. Paoletti, M. Meliga, G. Olivetti, M. Puleo, G. Rossi, L. Senepa, "10 Gbit/S Ultra-Low Chirp 1.55 $\mu\text{m}$  Directly Modulated Hybrid Fiber Grating - Semiconductor Laser Source", *23rd European Conference on Optical Communication ECOC '97*, Mo 3B. 22-25 September 1997, Edinburgh (UK).
- G. Rossi, R. Paoletti, M. Meliga, "SPICE simulation for analysis and design of fast 1.55  $\mu\text{m}$  MQW laser diodes", *IEEE Journal of Lightwave Technology*, Vol. 16, No. 7, July 1998.
- R. Paoletti, M. Agresti, G. Burns, G. Berry, D. Bertone, P. Charles, P. Crump, A. Davies, R.Y. Fang, R. Ghin, P. Gotta, M. Holm, C. Kompocholis, G. Magnetti, J. Massa, G. Meneghini, G. Rossi, P. Ryder, A. Taylor, P. Valenti and M. Meliga, "100 °C, 10 Gb/s directly modulated InGaAsP DFB lasers for uncooled Ethernet applications", post-deadline at *European Conference on Optical Communication ECOC '2001*, October 2001, Amstendam (NL).
- R. Paoletti, M. Meliga, "Uncooled, high speed DFB lasers for Gigabit Ethernet applications", invited paper at *SPIE'S International Symposia - Photonics West Optoelectronics 2002*, 19 - 25 Jan. 2002, S. José, CA, USA.
- R. Paoletti, M. Agresti, D. Bertone, L. Bianco, C. Bruschi, A. Buccieri, R. Campi, C. Dorigoni, P. Gotta, M. Liotti, G. Magnetti, P. Montangero, G. Morello, C. Rigo, E. Riva, D. Soderstrom, S. Stano, P. Valenti, M. Vallone, M. Meliga "Highly reliable and high yield 1300 nm InGaAlAs directly modulated ridge Fabry-Perot lasers, operating at 10 Gb/s, up to 110 °C, with constant current swing", Post deadline at Optical Fiber Conference OFC 2005, Anaheim (CA)
- R. Paoletti, M. Agresti, D. Bertone, C. Bruschi, S. Codato, C. Coriasso, R. DeFranceschi, P. Dellacasa, M. Diloreto, R. Y. Fang, P. Gotta, G. Meneghini, C. Rigo, E. Riva, G. Roggero, A. Stano, M. Meliga, 'Uncooled 20 Gb/s Direct Modulation of High Yield, Highly Reliable 1300 nm InGaAlAs Ridge DFB Lasers", Optical Fiber Conference OFC 2009